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PROCESS FOR THE FORMATION OF POLYHEDRAL OLIGOMERIC SILSESQUIOXANES

BACKGROUND OF THE INVENTION

This disclosure describes methods that enable the selective manipulation of the silicon-oxygen frameworks in polyhedral oligomeric silsesquioxane (POSS) cage molecules. It is desired to selectively manipulate the frameworks of POSS compounds because they are useful as chemical species that can be further converted or incorporated into a wide variety of chemical feed-stocks useful for the preparation of catalyst supports, monomers, polymers, and as solubilized forms of silica that can be used to replace fumed and precipitated silicas or in biological applications, and for surface modification. When incorporated into a polymeric material POSS can impart new and improved thermal, mechanical and physical properties to common polymeric materials.

A variety of POSS frameworks can be prepared in synthetically useful quantities via the hydrolytic condensation of alkyl- or aryl-trichlorosilanes. In most cases, however, hydrolytic condensation reactions of trifunctional organosilicon monomers afford complex polymeric resins and POSS molecules that are unsuitable for use in polymerization or grafting reactions because they do not possess the desired type or degree of reactive functionality. In light of the fact that many structurally well-defined silsesquioxane resins $[RSiO_{1.5}]$ and POSS molecules of the homoleptic formula $[(RSiO_{1.5})_n]_{\#}$ (where R= includes but is not limited to aliphatic, aromatic, olefinic or alkoxy groups and n = 4-14) can be prepared in good to excellent yields from readily available organosilicon monomers, there are enormous incentives for developing a methodology capable of converting these POSS species into systems bearing functionalities that are more desirable for polymerization, grafting, catalysis, or compatibilization with common organic resins. Examples of such desirable functionalities include but are not limited to: silanes, silylhalides, silanols, silylamines, organohalides, alcohols, alkoxides, amines, cyanates, nitriles, olefins, epoxides, organoacids, esters, and strained olefins.

Prior art in the silsesquioxane field has taught processes for the chemical manipulation of the organic functionalities (substituents denoted by R) contained on the silicon oxygen frameworks of polyhedral oligomeric silsesquioxanes. While these methods are highly useful for varying the organic functionality (substituents) contained on POSS molecules they are not always amenable to low-cost manufacturing nor do they offer the ability to selectively cleave and or manipulate the silicon-oxygen frameworks of such compounds. Thus, these methods are of no utility for transforming the multitude of readily available and low cost silane, silicate, polysilsesquioxane (aka/T-resins or T-type siloxanes) or POSS systems.

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Prior art has reported that bases (e.g., NaOH, KOH, etc.) could be used to both catalyze the polymerization of POSS into lightly networked resins or to convert selected polysilsesquioxane resins into homoleptic polyhedral oligomeric silsesquioxane structures. Marsmann et al have more recently shown that a variety of bases can be used to redistribute smaller homoleptic POSS cages into larger sized homoleptic cages. While there is precedent in the literature for treatment of silsesquioxanes and POSS systems with base, the previous art does not afford the selective manipulation of silicon-oxygen frameworks and the subsequent controlled production of POSS fragments, homoleptic POSS nanostructures, heteroleptic POSS nanostructures and functionalized heteroleptic POSS nanostructures. Furthermore, the prior art does not provide methods of producing POSS systems suitable for functionalization and subsequent polymerization or grafting reactions. This oversight in the prior art is reflective of the fact that the invention of POSS-based reagents, monomers and polymer technology has only recently been developed and consequently post-dates this prior art. Hence POSS compositions and processes relevant to the types of systems desired for POSS monomer/polymer technology were not envisioned in the prior art. Additionally the prior art does not demonstrate the action of bases on silane, silicate, or silsesquioxane feedstocks suitable for producing low-cost and high purity POSS systems.

>In contrast to the prior art (Brown et al. and Marsmann et al.), the processes taught here specifically enable the development of lower cost, high purity POSS systems bearing functionalities useful as derivitizable chemical reagents and feedstocks.

SUMMARY OF THE INVENTION

This invention teaches three processes that enable the manipulation and development of POSS compounds from readily available and low-cost silicon containing feedstocks. Examples of these low cost feedstocks include but are not limited to: Polysilsesquioxanes

[RSiO_{1.5}]_∞, homoleptic Polyhedral Oligomeric Silsesquioxanes (POSS) [(RSiO_{1.5})_n]_{∑#},

functionalized homoleptic POSS [(RSiO1.5)_m(RXSiO1.0)_n]_{\(\Si\)}, heteroleptic POSS

-[(RSiO1.5)_m(RSiO1.5)_m]_{\(\SiO1.5})_m functionalized heteroleptic POSS,[(RSiO1.5)_m(RXSiO1.0)_m]_{\(\SiO1.5})_m and polyhedral oligomeric silicates $[(XSiO_{1.5})_n]_{\Sigma_{\#}}$, and POSS fragments $[(RXSiO_{1.5})_n]$.

DEFINITION OF FORMULA REPRESENTATIONS FOR POSS NANOSTRUCTURES:

For the purposes of explaining this invention's processes and chemical compositions the following definition for representations of nanostructural-cage formulas is made:

Polysilsesquioxanes are materials represented by the formula $[RSiO_{1.5}]_{\infty}$ where $\infty = \text{degree of}$ polymerization within the material and R = organic substituent (H, cyclic or linear aliphatic

or aromatic groups that may additionally contain reactive functionalities such as alcohols, 1 esters, amines, ketones, olefins, ethers or halides). Polysilsesquioxanes may be either 2 homoleptic or heteroleptic. Homoleptic systems contain only one type of R group while 3 heteroleptic systems contain more than one type of R group. 4

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POSS nanostructure compositions are represented by the formula:

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 $[(RSiO_{1.5})_n]_{\Sigma_{\#}}$ for homoleptic compositions 8

 $-[(RSiO_{1.5})_{m}(RSiO_{1.5})_{n}]_{\Sigma_{\#}}$ for heteroleptic compositions

 $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$ for functionalized heteroleptic compositions

[(XSiO₁₋₅)]_{2#} for homoleptic silicate compositions

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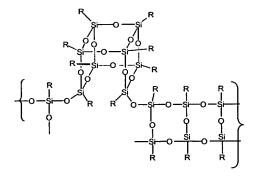
In all of the above R is the same as defined above and X includes but is not limited to OH, Cl, Br, I, alkoxide (OR), acetate (OOCR), peroxide (OOR), amine (NR2) isocyanate (NCO), and R. The symbols m and n refer to the stoichiometry of the composition. The symbol Σ indicates that the composition forms a nanostructure and the symbol # refers to the number of silicon atoms contained within the nanostructure. The value for # is usually the sum of m+n. It should be noted that Σ# is not to be confused as a multiplier for determining stoichiometry, as it merely describes the overall nanostructural characteristics of the POSS system (aka cage size).

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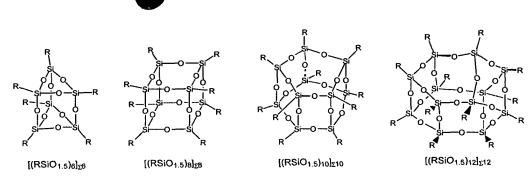
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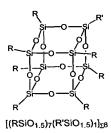
POSS Fragments are defined as structural subcomponents that can be assembled into POSS nanostructures and are represented by formula $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]$ Note the symbols $\Sigma \#$ are absent as these fragments are not polyhedral nanostructures.



Example of Polysilsesquioxane Resins [RSiO_{1.5}] ∞



Examples of Homoleptic POSS Systems [(RSiO_{1.5})]_{Σ #}



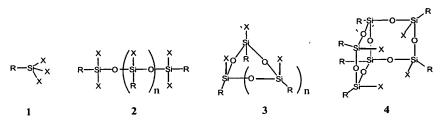
Example of a Heteroleptic POSS System $[(RSiO_{1.5})_m(R'SiO_{1.5})_n]_{\Sigma_{\#}}$

Example of a Functionalized Homoleptic POSS System $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$

 $[(\mathsf{RSiO}_{1.5})_3(\mathsf{R'SiO}_{1.5})_1(\mathsf{RXSiO}_{1.0})_3]_{\Sigma^7}$

 $Example \ of \ a \ Functionalized \ Heteroleptic \ POSS \ System \ [(RSiO_{1.5})_m (R'SiO_{1.5})_n (RXSiO_{1.0})_p]_{\Sigma\#}$

Example of a Polyhedral Oligomeric Silicate System $[(XSiO_{1.5})_n]_{\Sigma_{\#}}$



Fragment Examples: $RSiX_3$ (1), $[(RXSiO_{0.5})_n]$ (2), $[(RXSiO_{1.0})_n]$ (3), $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]$ (4)

Figure 1. Examples of Common Silsesquioxane, Silicate, POSS Nanostructures and Fragments.

GENERAL PROCESS VARIABLES APPLICABLE TO ALL PROCESSES

As is typical with chemical processes there are a number of variables that can be used to control the purity, selectivity, rate and mechanism of any process. Variables influencing the process for the conversion of polysilsesquioxanes $[RSiO_{1.5}]_{\infty}$ into POSS structures $[(RSiO_{1.5})_n]_{\Sigma_{\#}}$, $\frac{[(RSiO_{1.5})_m(RSiO_{1.5})_n]_{\Sigma_{\#}}}{[(RSiO_{1.5})_m(RSiO_{1.5})_n]_{\Sigma_{\#}}}$

 $[(RSiO_{1.5})_n]_{\Sigma\#}$, $[(RSiO_{1.5})_m(RSiO_{1.5})_n]_{\Sigma\#}$, $[(RSiO_{1.5})_m(RSiO$

Co-reagent Promoters

Specific chemical agents can be utilized to promote or enhance the effectiveness of the bases utilized in the processes. Specifically, nucleophilic base mixtures that work in combined fashion to firstly solubilize the silsesquioxane and secondly promote formation of the POSS nanostructure. Examples of such systems may include but are not limited to KOR where OR is an alkoxide, RMgX which include all common Grignard reagents, or alkalihalides such as LiI, or any of a variety of molten or fused salt media. In a similar fashion co-bases such as [Me₃Sn][OH] and [Me₄Sb][OH] have been shown to promote chemical transformations of POSS systems yet have not been utilized as a co-reagent in the formation of POSS cages. Alternatively, electrophilic promoters such as zinc compounds, (i.e. ZnI₂, ZnBr₂, ZnCl₂, ZnF₂, etc.) aluminum compounds, (i.e. Al₂H₆, LiAlH₄, AlI₃, AlBr₃, AlCl₃, AlF₃, etc.) boron compounds including (i.e. RB(OH)₂, BI₃, BBr₃, BCl₃, BF₃, etc.) which are known to play important roles in the solubilization and ring-opening

polymerization of cyclic silicones and in the ring-opening of polyhedral oligomeric silsesquioxanes.

Chemical Bases

The purpose of the base is to cleave the silicon-oxygen-silicon (Si-O-Si) bonds in the various silsesquioxane structures. The exact type of base, its hydration sphere, concentration, and solvent interactions all play important roles in the effectiveness of the base for cleaving the silicon-oxygen bonds. Proper understanding and control of conditions enable the selective cleavage and/or assembly of silsesquioxane, silicate, POSS, and POSS fragment systems in the desired manner. The base can also assist in the assembly of POSS fragments.

There are a wide range of bases that can be used in the processes and these include but are not limited to: hydroxide [OH], organic alkoxides [RO], carboxylates [RCOO], amides [RNH], carboxamides [RC(O)NR], carbanions [R] carbonate [CO₃], sulfate [SO₄], phosphate [PO₄], biphosphate [HPO₄], phosphourus ylides [R₄P], nitrate [NO₃], borate [B(OH)₄], cyanate [OCN], fluoride [F], hypochlorite [OCl], silicate [SiO₄], stannate [SnO₄], basic metal oxides (e.g. Al₂O₃, CaO, ZnO etc.), amines R₃N and amine oxides R₃NO, and organomtallics (e.g. RLi, R₂Zn, R₂Mg, RMgX etc.). Furthermore, the processes taught here are not limited to the above-mentioned bases; rather any reagent can be employed which produces a pH spanning the range from 7.1 to 14.

Alternatively mixtures of bases may also be utilized to carryout the process. One advantage of such an approach is that each of the bases in a given mixture can serve different functions. For example in a mixed base system one base can be used to cleave silicon-oxygen bonds or silicon-X bonds while a second base is used to assemble the POSS structure. Thus synergies can exist amongst several types of bases and these can be utilized to the advantage and refinement of these processes.

Silicon-oxygen Ring Size, Ring Type and Cage sizes

The processes discussed in this disclosure are not limited to the formation of specific sizes of POSS cages (i.e Σ # in $[(RSiO_{1.5})_n]_{\Sigma}$ #). Similarly the processes should not be limited to specific types of silsesquioxanes (i.e. resins, cages or fragments). They can be carried out to manufacture POSS cages containing four to eighteen or more silicon atoms in the silicon-oxygen framework. It has been noted that the silicon-oxygen ring size contained within such POSS systems does however affect the rate at which cage silicon-oxygen ring opening can occur. For example rings containing three silicon atoms and three oxygen atoms as in Formula 1 appear to open faster than the larger rings containing 4 silicon atoms and 4 oxygen atoms. The relative rate for the opening of POSS silicon-oxygen rings appears to be six member rings with three silicon atoms> eight member rings with four silicon atoms>ten member rings with five silicon atoms> twelve member rings with six silicon atoms. Selective

ring opening processes therefore can be controlled through the use of the appropriate base and knowledge of this information allows the user of these processes to control selective formation of POSS molecules.

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Effect of the Organic Substituent, Process Solvents and Process Temperatures

The processes described in this disclosure are not limited to POSS systems bearing specific organic groups (defined as R) attached to the silicon atom of the silicon-oxygen ring systems. They are amenable to silsesquioxane feedstocks bearing a wide variety of organic groups (R = as previously defined) and functionalities (X= as previously defined). The organic substituent R does have a large effect on the solubility of both the final product and the starting POSS material. Therefore, it is envisioned that the different solubilities of the starting silsesquioxanes and POSS products can be used to facilitate the separation and purification of the final reaction products. We currently find no limitation of the process with respect to the type of solvent used and the processes have been carried out in common solvents including but not limited to ketones, ethers, dimethylsulfoxide, CCl4, CHCl3, CH₂Cl₂, fluorinated solvents, aromatics (halogenated and nonhalogenated), aliphatic (halogenated and nonhalogenated). Other processes can be carried out in supercritical fluids including but not limited to CO2, H2O, and propane. The variables of solvent type, POSS concentration, and process temperature should be utilized in the standard way to match the specific cage opening process to the equipment available. Preferred solvents for the processes are THF, MIK, and toluene. In many cases the solvent is an integral component of the process, which to enables the base to act on the specific silsesquioxane system, hence solvent effects greatly influence the degree of ionization of the base used in these processes.

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Process I: Formation of POSS Systems from Polymeric Silsesquioxanes.

The current methods of preparing POSS molecules from the acid catalyzed condensation of alkyltrichlorosilanes (RSiCl₃) is inefficient in that it produces mixtures of POSS cage species homoleptic (POSS) $[(RSiO_{1.5})_n]_{\Sigma_{\#}}$, functionalized homoleptic POSS $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$, heteroleptic POSS $[(RSiO_{1.5})_m(RSiO_{1.5})_n]_{\Sigma_{\#}}$ heteroleptic POSS $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_\#}$ and polymeric silsesquioxanes $[RSiO_{1.5}]_{\infty}$. In some cases the undesired polymeric silsesquioxanes are produced in as much as 75% yield. It is therefore advantageous to develop a process that can efficiently convert $[RSiO_{1.5}]_{\infty}$ into desirable POSS nanostructures or into POSS fragments [(RXSiO_{1.5})_n]. Such a process will serve to not only reduce the amounts of hazardous waste produced in such reactions but will also reduce the production costs for POSS systems.

The process developed utilize bases (as defined previously), in particular hydroxide hydroxide, lithium hydroxide, sodium hydroxide, potassium bases (e.g.

benzyltrimethylammonium hydroxide, tetramethyl ammonium hyrdoxide etc) to convert
 polymeric silsesquioxanes [RSiO_{1.5}]_∞ into homoleptic (POSS) [(RSiO_{1.5})_n]_{Σ#}, functionalized
 homoleptic POSS [(RSiO_{1.5})_n(RXSiO_{1.0})_n]_{Σ#}, heteroleptic POSS [(RSiO_{1.5})_m(R'SiO_{1.5})_n]_{Σ#},
 and functionalized heteroleptic POSS [(RSiO_{1.5})_m(R'XSiO_{1.0})_n]_{Σ#}.

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In the current process polymeric silsesquioxane $[RSiO_{1.5}]_{\infty}$ is dissolved or suspended in a technical grade solvent such as acetone or methylisobutyl ketone, and subsequent addition of an aqueous or alcoholic solution of base is carried out with stirring. Sufficient base should be added to the reaction mixture so as to produce a basic solution (pH 7.1-14). The reaction mixture is stirred at room temperature for 3 hours followed by heating to reflux for an additional 3-12 hours. During this time the desired POSS cages generally precipitate from the reaction medium due to their insolubility in the reaction medium. This precipitation aids in the isolation of the desired products and ensures that the products (such as the functionalized POSS species) do not undergo further reaction. In some cases it is desirable to reduce the volume of solvent by distillation or by reduced pressure in order to increase product yields or to isolate soluble POSS products. The desired POSS product is collected by filtration or decantation and can be purified through exhaustive washing with water.

We have found that hydroxide [OH] bases are highly effective at concentrations of 1-10 equivalents (the preferred range is 2-5 equivalents per silicon atom) per mole of silicon for the conversion of aliphatic and aromatic polysilsesquioxanes $[RSiO_{1.5}]_{\infty}$ into homoleptic (POSS) $[(RSiO_{1.5})_n]_{\Sigma_{\#}}$, functionalized homoleptic POSS $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$ heteroleptic POSS $[(RSiO_{1.5})_m(RSiO_{1.5})_m(RSiO_{1.5})_n]_{\Sigma_{\#}}$, and functionalized heteroleptic POSS $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$ Hydroxyl-bases are particularly effective for producing $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$ POSS species. We have found that milder bases such as acetate and carbonate are more effective at converting $[RSiO_{1.5}]_{\infty}$ systems bearing vinyl or allyl groups. It is also recognized that the use of other co-reagents may be used to promote the formation of POSS species from this process.

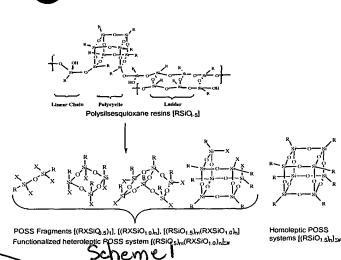


Figure 2. Illustration of Process I where polymeric silsesquioxane resins are converted into POSS fragments and nanostructures.

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For the above reaction scheme the polymeric silsesquioxane resin is converted into either POSS fragments or nanostructured POSS cage species depending on the type of base and conditions employed. The conversion of polysilsesquioxanes [RSiO,]∞ to POSS-species (homoleptic $[(RSiO_{1.5})_m]_{\Sigma_{\#}}$, functionalized homoleptic $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$, heteroleptic I(RSiO_) (RSiO_) and functionalized heteroleptic (RSiO_) (RXSiO_) | z_#) or into POSS-fragments [(RXSiO_{1,5})_n] can be selectively controlled through manipulation of the process variables discussed above. The process can be conducted using a polysilsesquioxane resin which may contain only one type of R group to produce homoleptic $[(RSiO_{15})_n]_{\Sigma_{\#}}$ products. Alternatively the process can be carried out using polysilsesquioxane resins containing more than one type of R group or with mixtures of polysilsesquioxanes in which each contains different R groups to afford heteroleptic (RSiO_{1.5})_m(RSiO_{1.5})_n]_{2#} products. For the above reaction scheme in which mixtures of homoleptic POSS cages (i.e. R of one POSS cage \neq R of the second POSS cage) are substituted for the polysilsesquioxane resin the process effectively converts mixtures of homoleptically substituted POSS cages into heteroleptic POSS cages (functionalized and nonfunctionalized) that contain statistical distributions of different R groups per cage. In most cases the POSS fragments and various homo or heteroleptic nanostructured POSS species can be separated from one another through crystallization, or extractions by utilizing the differences in solubility between the reaction products and the starting silsesquioxane.

The purpose of the base in this process is to cleave silicon-oxygen bonds in the starting silsesquioxane and thereby allow for, as well as aid in the rearrangement and formation of the various POSS fragments, homoleptic and heteroleptic species. The strength of the base and the base-solvent-silsesquioxane interaction are critical factors, which enable

control over the type of products formed in these reactions. For example, increasing the basicity of the medium affords the production of POSS fragments while less basic conditions coupled with exclusion of water promote the formation of nonfunctionalized POSS species. Formation of functionalized POSS systems are favored by carrying out the process at an intermediate pH with scarce amounts of water for shorter periods of time.

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Process II: Reactions between POSS Systems and Silsesquioxane/Siloxane Fragments.

The process developed utilized bases (as defined previously) to convert fragments and functionalized POSS nanostructures $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$ into alternate functionalized POSS nanostructures $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$. In the process a POSS fragment is dissolved or suspended in acetone, benzene or alcoholic solvents after which a solution of base is added with stirring. In general the reaction conditions employed in this process are milder than those used in Process 1 and can utilize both hydroxide and nonhydroxide bases, while the molar ratio of base relative to silicon is 1:10 (with 1:1 or 1:2 ratio being preferred).

$$R-S \stackrel{X}{\swarrow} X$$

$$R-S \stackrel{X}{\swarrow} X$$

$$R-S \stackrel{X}{\longleftrightarrow} Q = S \stackrel{X}{\longleftrightarrow$$

Fragments

POSS Cages and Functionalized POSS

POSS Fragments

POSS Cages and Functionalized POSS

$$\begin{array}{c} X \\ Si \\ O \\ R \\ R \\ \end{array}$$

POSS Fragments 2 POSS Cages and Functionalized POSS Fragments converted into POSS cages.

The purpose of the base in this process is to cleave silicon-oxygen bonds in the starting POSS fragments. The base may also aid in the assembly of POSS structures from the fragments. A number of different bases (as defined previously) can be used to convert POSS fragments into POSS compounds. The net reaction results in the assembly of POSS fragments into POSS nanostructures, having either homoleptic or heteroleptic composition. Additionally, the resulting POSS cages may contain functional groups (i.e.

 $\{(RSiO_{1.5})_{m}(RXSiO_{1.0})_{n}\}_{\Sigma\#}$

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 When mixtures of POSS fragments are utilized they are incorporated statistically into the POSS structure and their final composition is based on the stoichiometry of the starting POSS fragments. In some cases the statistical degree of substitution between these groups is governed by isomorphism resulting from the nearly identical topological shape of the R group (e.g. vinyl and ethyl). Isomorphic governance is often observed for closely related R groups (e.g. allyl and propyl etc.) however, on occasion the trend is not followed due to other factors such as rate of reaction, reagent addition, or solubility between the various POSS fragments and products. For example the reaction of 1 equivalent of EthylundeconoateSi(OMe)₃ or VinylSi(OMe)₃ with 7 equivalents of MeSi(QMe)₃ results in a molecule of formula 2 of the composition $[(ViSiO_{1.5})_1(MeSiO_{1.5})_7]_{\Sigma_8}$ or $[(EthylundeconoateSiO_{1.5})_1(MeSiO_{1.5})_7]_{\Sigma_8}$ despite the topological dissimilarity between the R groups.

In many cases the desired homo or heteroleptic nanostructured POSS species can be separated from one another via crystallization, extraction or by utilizing differences in the solubilities of the products and the starting POSS fragments.

An extension of this process is the action of base on functionalized POSS nanonostructures (i.e. $\frac{[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{2m}}{[(RXSiO_{1.0})_n]_{2m}}$. It should be noted that these systems are chemically similar to a POSS fragments in terms of their chemical composition. They are different however in their topology and physical properties such as melting point, solubility and volatility.

Figure 4 illustrates actual reactions that use the conditions described in Process II as proof that the bases and conditions described in Process II are effective for the conversion of functionalized POSS cages (i.e. $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$) desired POSS structures. It should also be noted that in most cases these process results in an increase in the number of functionalities (X) on a POSS nanostructure while at the same time maintaining the original number of silicon atoms contained within the starting nanostructural framework. This can be desirable for a variety of subsequent synthetic product manipulations and derivations.

Figure 4 illustrates actual reactions that use the conditions described in Process II as proof that the bases and conditions described in Process II are effective for the conversion of functionalized POSS cages (i.e. $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$) desired POSS structures. It should also be noted that in most cases these process results in an increase in the number of

1 functionalities (X) on a POSS nanostructure while at the same time maintaining the original

2 number of silicon atoms contained within the starting nanostructural framework. This can be

3 desirable for a variety of subsequent synthetic product manipulations and derivations.

The first example in Figure 4 illustrates the selectivity for the cleavage of 6 membered silicon-oxygen rings in the presence of 8 membered silicon-oxygen rings by the base, to afford the trifunctionalized POSS species. This reaction is driven by the release of greater ring strain energy from the cleavage of the 6 membered silicon-oxygen ring vs. cleavage of the 8 membered silicon-oxygen ring and is thermodynamically favorable. In the second example the energy of the twisted conformation is relieved upon cleavage to form a more open structure.

A final alternate of process II and one that is of great utility is that it can also allow for the incorporation of POSS fragments into existing POSS and POSS silicate nanostructures. This is a very important and useful aspect of this process because it allows for the expansion of both POSS and POSS silicate cage species. This is analogous to a carbon-carbon bond forming processes in organic systems. Hence this process can be utilized to prepare larger POSS nanostructures as well as POSS nanostructures having previously inaccessible sizes. Of particular importance is the use of this process to prepare nanostructures having odd as well as even numbers of silicon atoms.

Figure 5. Silsesquioxane/siloxane fragments being inserted into POSS Cages

Subc8 The net reaction in the examples shown in Figure 5 is cleavage of an Si-O-Si bond in the POSS or POSS silicate nanostructure and insertion of the POSS fragment. This reaction results in the expansion of the silicon-oxygen ring in the POSS nanostructured product. Note that the ring expansion in these reactions is in some cases favored thermodynamically through relief of ring strain in the silsesquioxane starting material. For example, the reaction of 1 equivalent of Vinyl(OMe)₃ with $[((c-C_6H_{11})SiO_{1.5})_6]_{\Sigma_6}$ results in POSS molecule having the composition $[((c-C_6H_{11})SiO_{1.5})_4(c-C_6H_{11})(HO)SiQ_{1.0})_2(ViSiO_{1.0})_1]_{\Sigma_7}$

Mixtures of bases may also be utilized to carryout the process. One advantage of such an approach is that the use of different types of base in combination could serve different functions. For example one base may be particularly useful for the cleavage of Si-X groups while the second base may function in the assembly of POSS fragments into POSS nanostructures. Synergistic effects between different types of base can also be expected.

Particularly important is the use of mixtures of POSS fragments (i.e. where R of one fragment $\neq R$ of the other fragment) or POSS fragments having more than one type of R group. Use of mixed fragments or fragments having mixed R groups affords heteroleptic POSS species $[(RSiO_{1.5})_m(RSiO_{1.5})_n]_{\Sigma_{\#}}$ which contain more than one type of R group. In general the POSS nanostructured products formed contain a statistical mixture of R which is determined by the stoichiometry of the starting fragments. As a result, numerous isomers are possible.

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Process III: Selective Opening, Functionalization and Rearrangement of POSS **Nanostructures**

This processes utilizes bases (as defined previously) and POSS nanostructures having homoleptic $[(RSiO_{1.5})_n]_{\Sigma_{\#}}$ and heteroleptic $[(RSiO_{1.5})_m(RSiO_{1.5})_n]_{\Sigma_{\#}}$ compositions.

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process allows for the conversion of low cost and easily produced unfunctionalized POSS 1

functionalized POSS systems of the type 2 into more desirable nanostructures

 $[(RSiO_{1.5})_{\scriptscriptstyle m}(RXSiO_{1.0})_{\scriptscriptstyle n}]_{\Sigma\#}. \quad POSS \ nanostuctures \ of \ the \ type \ [(RSiO_{1.5})_{\scriptscriptstyle m}(RXSiO_{1.0})_{\scriptscriptstyle n}]_{\Sigma\#} \ can be considered as a constant of the property of t$ 3

be used as stand alone chemical reagents or further derivatized to provide a diverse array of 4

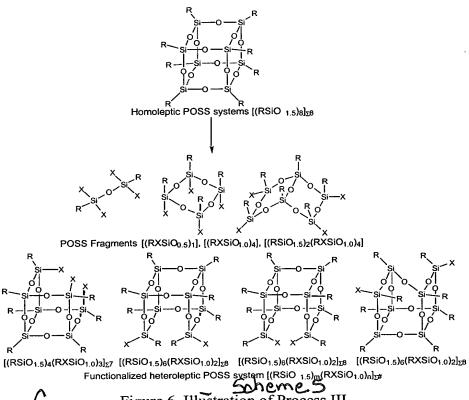
other POSS nanostructures. This process provides an entirely new synthetic route for the 5

preparation of very important and useful incompletely condensed trisilanol reagents 6

 $[(RSiO_{1.5})_4(RXSiO_{1.0})_3]_{\Sigma_7}$ in particular where X = OH. 7

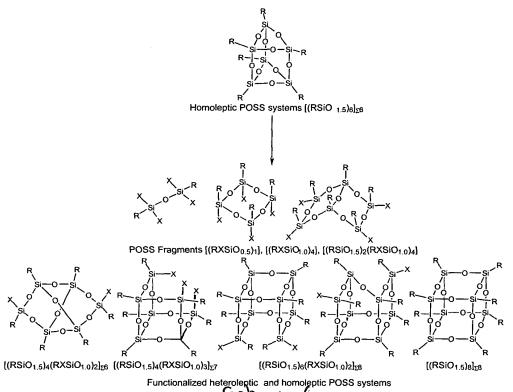
Homoleptic POSS nanostructures [(RSiO_{1.5})_n]_{E#} are readily converted into POSS 8 panostructures having the formula $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]_{\Sigma_{\#}}$, as well as POSS fragments having the formula $RSiX_3$, $[(RXSiO_{0.5})_n]$, $[(RXSiO_{1.0})_n]$, or $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]$ through the use of bases as shown in Figure 6. Note that all possible geometric and stereochemical

isomers for each product are not shown. 12



Sub Clo Furthermore as a variation of this process it is possible to interconvert various sizes of POSS nanostructures. For example, with the proper addition of base $[(RSiO_{1.5})_6]_{\Sigma_6}$ can be either cleaved into a smaller POSS fragments (e.g. [RSiX₃], [(RXSiO_{0.5})_n], [(RXSiO_{1.0})_n], or $[(RSiO_{1.5})_m(RXSiO_{1.0})_n]$ or functionalized into heteroleptic POSS nanostructures of the same

size (ê.g. $[(RSiO_{1.0})_2]_{\Sigma_6}$) or larger (e.g. $[(RSiO_{1.5})_4(RXSiO_{1.0})_3]_{\Sigma_7}$) as shown in Figure 2 6.



Scheme C Figure 7. Illustration of Process III

As a variation of the above it is recognized that this process can utilize mixtures and distributions of POSS cages as well as polyhedral oligomeric silicate species (e.g. [((CH₃)₃SiO)SiO_{1.5})₆]_{Σ6}, [((CH₃)₄NO)SiO_{1.5})₆]_{Σ6}, [((CH₃)₄NO)SiO_{1.5})₈]_{Σ8}, [((CH₃)₄NO)SiO_{1.5})₈]_{Σ8}. In such cases the base effectively converts cages of several sizes into

functionalized and nonfunctionalized heteroleptic POSS nanostructures as shown in Figure 7.

This represents an entirely new synthetic route for the preparation of the very useful

7 incompletely condensed trisilanol reagents $\{(RSiO_{1.5})_4(RXSiO_{1.0})_3\}_{\Sigma_7}$ in particular where X =

8 OH.

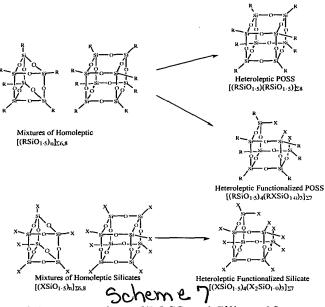


Figure 8. Illustration of the conversion of POSS and Silicate Nanostructures - Process III

nanostructures. POSS nanostructures bearing more than one type of R group per cage [(RSiO_{1.5})_m(RSiO_{1.5})_n]_{\(\Si\)} are readily converted through the use of base into functionalized POSS nanostructures [(RSiO_{1.5})_n(RXSiO_{1.0})_n]_{\(\Si\)}. Note that all possible geometric and stereochemical isomers are not shown.

Functionalized heteroleptic POSS system [(RSiO $_{1.5}$)m(RXSiO $_{1.0}$)n] $_{2\#}$

Figure 9. Illustration of the conversion of POSS Nanostructures - Process III

The action of base in the described in the preceding paragraph can also be controlled selectively so that silicon atoms can be removed entirely from the silicon oxygen framework of a polyhedral oligomeric silsesquioxane. This represents an entirely new synthetic route for the preparation of the very useful incompletely condensed trisilanol reagents such as $[(RSiO_{1.5})_4(RXSiO_{1.0})_3]_{\Sigma\#}$ where X = OH in particular. Note that not all stereochemical and geometrical isomers have been shown.

ADDITIONAL MATERIAL - SECTION B: ISOMERS OF POSS SYSTEMS

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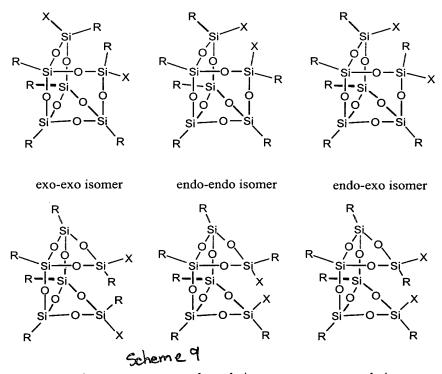
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METHODS FOR CONTROLLING STEREOCHEMISTRY

Given the three dimensional, nanoscopic nature of POSS systems it is important to realize that a number of isomeric forms for any given formula may be produced by the processes taught in this work. The stereochemistry of these isomers can be controlled by the through methods taught in this patent however, in some cases geometrical isomers will still exist. A number of examples are provided to convey our acknowledgement of the presence of such isomers and that we in no way limit our claims to any one specific stereochemical or geometrical isomer.

Six isomers are possible for difunctional, incompletely condensed POSS nanostructures $[(RSiO_{1.5})_4(RXSiO_{1.0})_2]_{\Sigma_6}$ as shown in Figure 10.



exo-exo isomer endo-endo isomer exo-endo isomer

Figure 10. Isomers for disfunctional, incompletely condensed POSS nanostructures.

[(RSiO_{1.5})₄(RXSiO_{1.0})₂]₂₈

EXAMPLES

NMR spectra were recorded on Omega-500 (¹H, 500 MHz; ¹³C, 125 MHz; ²⁹Si, 99 MHz). tetrahydrofuran, methylisobutyl ketone were distilled prior to use. All other solvents were used as purchased without purification.

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Examples for Process I. The conversion of polysilsesquioxanes into POSS fragments and nanostructures.

 $[(C_6H_5)SiO_{1.5}]_{\infty}$ resin. of $[((C_6H_5)SiO_{1.5})_8]_{\Sigma_8}$ from **Synthesis** Tetramethylammonium hydroxide (2.0 mL, 5.57 mmol) was added to $[(C_6H_5)SiO_{1.5}]_{\infty}$ resin (13.0 g, 100.6 mmol) in toluene (100 mL) at room temperature. The reaction mixture was heated to 80 °C for 12 hours, then cooled to room temperature, acidified with 1N HCl, and filtered to give 12.065 g of $[((C_6H_5)SiO_{1.5})_8]_{\Sigma_8}$ as a white solid. Product was verified by EIMS which shows a molecular ion at 1032.5 amu along with daughter ions corresponding to loss of one, two, and three phenyl groups, respectively, at 954.7, 877.4, and 800.6 amu. The above procedure can be modified for the continuous and batch production. Alternately, benzene, acetone, and methyl ethyl ketone can also be used as solvents for this reaction in place of toluene and KOH can be used instead of tetraalkylammonium bases. In addition, phenyltrimethoxysilane can be used in place of phenyl resin to prepare $[((C_6H_5)SiO_{1.5})_8]_{\Sigma_8}$.

Synthesis of $[((C_6H_5)SiO_{1.5})_{12}]_{\Sigma_{12}}$ from $[(C_6H_5)SiO_{1.5}]_{\infty}$ resin. Potassium hydroxide (46.5 g, 829 mmol) was added to $[(C_6H_5)SiO_{1.5}]_{\infty}$ resin (1000 g, 7740 mmol) in THF (7.8L) at roomtemperature. The reaction mixture was heated to reflux for 2 days then cooled to room temperature and filtered to give 443 g of $[((C_6H_5)SiO_{1.5})_{12}]_{\Sigma_{12}}$ as a microcrystalline white solid. Additional $[(C_6H_5)SiO_{1.5}]_{\infty}$ resin (912 g, 7059 mmol) was added to the reaction mixture and the solution was heated to reflux for 2 days followed by cooling to room temperature and filtration to give 851 g of $[((C_6H_5)SiO_{1.5})_{12}]_{\Sigma_{12}}$ as a microcrystalline white solid. Characterization was accomplished by EIMS which shows a molecular ion at 1548.2 amu. The above procedure can be modified for the continuous and batch production. Alternately, methylene chloride can also be used as a solvent for this reaction in place of THF and tetraalkylammonium bases can be used instead of KOH. In addition, phenyltrimethoxysilane can be used in place of $[(C_6H_5)SiO_{1.5}]_{\infty}$ resin to prepare $[((C_6H_5)SiO_{1.5})_{12}]_{\Sigma_{12}}$.

Synthesis of $[(c-C_5H_9)SiO_{1.5}]_{\Sigma_8}$ from $[(c-C_5H_9)SiO_{1.5}]_{\infty}$ resin. A 1.80 gram sample of resin was dissolved into 90 ml of acetone and 90 mg of NaOH was added to the reaction

mixture. The mixture was allowed to stir for 3 hours at room temperature and then was heated to reflux overnight. The solution was then cooled and filtered to obtain 1.40 g (77% yield) of pure product. The white microcrystalline powder was confirmed by X-ray diffraction and by HPLC relative to authentic sample.

Synthesis of $[((CH_2=CH)SiO_{1.5})_8]_{\Sigma_8}$ from $[(CH_2=CH)SiO_{1.5}]_{\infty}$ resin and $[Si_8O_{20}][NMe_4]_{\Sigma_8}$. A 0.63 g sample of resin and 2.22g of tetramethylammonium silicate salt were dissolved into 20 ml of ethanol and NMe₄OH was added to the reaction mixture until it became highly basic (pH~12). The mixture was allowed to stir for 6 days at room temperature and then was filtered to obtain 1.9 g of $[((CH_2=CH)SiO_{1.5})_8]_{\Sigma_8}$. Alternately a distribution of cages of $[((CH_2=CH)SiO_{1.5})_n]_{\Sigma_n}$ where n=8, 10, 12, 14 can be prepared in a similar manner from the reaction of $CH_2=CHSi(OCH_3)_3$ in cyclohexane with NMe₄OH followed by azeotropic distillation of water and methanol. The resulting white solid product $[(CH_2=CH)SiO_{1.5}]_{\Sigma_{8-14}}$ is obtained in 40% yield and is highly desirable as it is highly soluble in common solvents/reagents and melts at approximately 150°C.

Synthesis of $[((c-C_6H_9)SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4]_{\Sigma_8}$: In a typical reaction, a mixture of (cyclohex-3-enyl)trichlorosilane and cyclohexyltrichlorosilane were added with vigorous stirring to a solution of methanol (200 mL) and water (5 mL). The mixture was then refluxed for 2 days. Upon cooling, volatiles were removed in vacuum to afford a resin containing both cyclohexyl-Si and cyclohex-3-enyl-Si groups. Base catalyzed redistribution of this resin was accomplished by refluxing for 48 h in methyl isobutyl ketone (25 ml) with enough $C_6H_5CH_2N(CH_3)_3OH$ to produce a strongly basic solution (ca. 2 mL of 40% solution in MeOH). Evaporation of the solvent (25°C, 0.01 Torr) gave a white resinous solid, which was stirred with acetone (15 mL) and filtered to afford a mixture $[((R)SiO_{1.5})_n((R')SiO_{1.5})_n]_{\Sigma_8}$ frameworks possessing both cyclohexyl and cyclohex-3-enyl groups. Isolated yields are typically 70-80%.

Note: Excluding enantiomers, there are $22 [((R)SiO_{1.5})_n((R')SiO_{1.5})_n]_{\Sigma_8}$ frameworks with the formula $(cyclohexyl)_n(cyclohex-3-enyl)_{8-n}Si_8O_{12}$ $(0 \le n \le 8)$. All are presumed to be present in the product mixture. The relative percentage of each compound is most dependent on the relative amounts of (cyclohex-3-enyl)trichlorosilane and cyclohexyltrichlorosilane used in the reaction, but it may also depend on other factors. The high-resolution ²⁹Si NMR spectrum (C_6D_6) of each product mixture exhibits a series of well-resolved resonances for framework Si atoms possessing cyclohexyl and cyclohexenyl groups. The chemical shifts of these resonances are constant, but the relative intensities of the resonances depend on the amount of $(cyclohex-3-enyl)SiCl_3$ and $cyclohexylSiCl_3$ used in the reaction. The product is clearly a mixture of $[((c-C_6H_{11})SiO_{1.5})_n((c-C_6H_9)SiO_{1.5})_n]_{\Sigma_8}$ frameworks. The following



1	chemical	shift	assignments (in C_6D_6)	were made based on c	omparis	sons to pure, authentic
2	samples	of	$[((c-C_6H_{11})SiO_{1.5})_8]_{\Sigma_8},$	$[((c-C_6H_9)SiO_{1.5})_8]_{\Sigma_8}$	and	$[((c-C_6H_{11})SiO_{1.5})_n((c-C_6H_{11})SiO_{1.5})]$
3	$C_6H_9)SiO_{1.5})_n]_{\Sigma_8}$:					
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Si-cyclohexenyl groups with three Si-cyclohexyl nearest neighbors: δ -67.40 Si-cyclohexenyl groups with two Si-cyclohexyl nearest neighbors: δ –67.46 Si-cyclohexenyl groups with one Si-cyclohexyl nearest neighbors: δ –67.51 Si-cyclohexenyl groups with zero Si-cyclohexyl nearest neighbors: δ –67.57 Si-cyclohexyl with three Si- cyclohexenyl groups: δ -67.91 Si-cyclohexyl with two Si- cyclohexenyl groups: δ -67.97 Si-cyclohexyl with one Si- cyclohexenyl groups: δ -68.02

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A sample prepared by reacting equimolar amounts (0.0125 mol) of (cyclohex-3enyl)trichlorosilane and cyclohexyltrichlorosilane as described above exhibited all 8 resonances with relative integrated intensities of approximately 4:17:17:5:4:21:22:10. A ¹³C NMR spectrum of the same sample (in CDCl₃) resembles a superposition of spectra for pure $[((c-C_6H_{11})SiO_{1.5})_8]_{\Sigma_8}$ and $[((c-C_6H_9)SiO_{1.5})_8]_{\Sigma_8}$, except that resonances for ^{13}C nuclei close to the Si₈O₁₂ framework are much broader due to the overlap of many resonances with slightly different chemical shifts: δ 127.45 (br m), 127.07, 27.47, 26.85, 26.63, 25.51, 25.08, 23.15, 22.64, 18.68. Analogous results were observed when $[((c-C_6H_{11})SiO_{1.5})_n((c-C_6H_9)SiO_{1.5})_n]_{\Sigma_8}$ mixtures were prepared using the following ratios of (cyclohex-3-enyl)trichlorosilane and cyclohexyltrichlorosilane:

Si-cyclohexyl with zero Si- cyclohexenyl groups: δ -68.08

Entry	(cyclohex-3-enyl)SiCl ₃	cyclohexylSiCl ₃		
1	2.7 g (12.5 mmol)	2.72 g (12.5 mmol)		
2	2.7 g (12.5 mmol)	8.18 g (37.5 mmol)		
3	2.7 g (12.5 mmol)	10.88 g (50 mmol)		
4	6.47 g (30 mmol)	9.79 g (45 mmol)		
5	1.35 g (6.25 mmol)	9.52 g (44 mmol)		
6	5.82 g (27 mmol)	9.79 g (45 mmol)		
7	0.68 g (3.13 mmol)	9.52 g (44 mmol)		

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1 Synthesis of $[(c-C_6H_9)SiO_{1.5}]_{\Sigma_8}$: A charge of (cyclohex-3-enyl)trichlorosilane (10.78) 2 g, 0.05 mol) was added with vigorous stirring to a solution of methanol (200 mL) and water (5 mL). The mixture was then refluxed overnight. Upon cooling, volatiles were removed in 3 vacuo to afford $[((c-C_6H_9)SiO_{1.5})_n]_{\infty}$ resin in quantitative yield. The ²⁹Si $\{^1H\}$ NMR spectrum 4 of the resin exhibits a broad featureless resonance characteristic of silsesquioxane resins and 5 no sharp resonances attributable to discrete polyhedral silsesquioxanes (e.g., $[((R)SiO_{1.5})_n]_{\Sigma_n}$ 6 with n = 6, 8, 10, 12, 14). Base catalyzed redistribution of $[((c-C_6H_9)SiO_{1.5})_n]_{\infty}$ resin was 7 accomplished by refluxing for 48 h in methyl isobutyl ketone (25 ml) with enough 8 9 C₆H₅CH₂N(CH₃)₃OH to produce a strongly basic solution (ca. 2 mL of 40% solution in 10 MeOH). Evaporation of the solvent (25°C, 0.01 Torr)) gave a white resinous solid, which was stirred with acetone (15 mL) and filtered to afford $[((c-C_6H_9)SiO_{1.5})_8]_{\Sigma_8}$ in 80% yield 11 (5.33 g) as a white, microcrystalline solid. Characterization data: ¹H NMR (500.2 MHz, CDCl₃, 300 K) δ 5.76 (br s, 2 H), 2.09 (br m, 4 H), 1.92 (br m, 4 H), 1.52 (br m, 1 H), 1.08 (br m, 1 H). 13 C NMR (125.8 MHz, CDCl₃, 300 K) δ 127.33, 127.08, 25.46, 25.03, 22.60, 18.60. $^{29} Si$ NMR (99.4 MHz, $C_6 D_6$, 300 K) δ -67.4. The product was also characterized by a single crystal X-ray diffraction study.]

Synthesis of $[(((CH_3)_2CH)SiO_{1.5})_8]_{\Sigma_8}$: Water (1 mL) was added carefully with vigorous stirring to a solution of (CH₃)₂CHSiCl₃ (6.15 g, 34.8 mmol) in methanol (100 mL). The solution was then refluxed for 24 h. Upon cooling, the solvent was evaporated to afford a quantitative yield of $[i-PrSiO_{3/2}]_n$ resin as a pale yellow liquid. The $^{29}Si\{^1H\}$ NMR spectrum of the resin exhibits a broad envelope of resonances characteristic of silsesquioxane resins and indicates that very little, if any, discrete polyhedral silsesquioxanes (e.g., $[((CH_3)_2CH)SiO_{1.5}]_n$ with n = 6, 8, 10, 12, 14) are present. Base catalyzed redistribution of the [((CH₃)₂CH)SiO_{1.5}]_n resin was accomplished by refluxing for 6 h in methyl isobutyl ketone (25 ml) with water (1.4 mL) and enough C₆H₅CH₂N(CH₃)₃OH to produce a strongly basic solution (ca. 1 mL of 40% solution in MeOH). The crude equilibration mixture was diluted with Et₂O (200 mL), washed several times with water, dried over anhydrous MgSO₄ and concentrated to afford $[(((CH_3)_2CH)SiO_{1.5})_8]_{\Sigma_8}$ as a white microcrystalline powder. The yield after one equilibration is typically 15-30%, but additional $[(((CH_3)_2CH)SiO_{1.5})_8]_{\Sigma_8}$ can be obtained by base-catalyzed redistribution of $[((CH_3)_2CH)SiO_{1.5}]_{\infty}$ resin present in the mother liquors. The compound prepared in this fashion is identical to [(((CH₃)₂CH)SiO_{1.5})₆]_{5.6} prepared via the method described by Unno (Chemistry Letters 1990, 489) Characterization data: 1 H NMR (500.2 MHz, CDCl₃, 300 K) δ 1.036 (d, J = 6.9 Hz, 48 H, CH₃); 0.909 (sept, J

1 = 7.2 Hz, 8 H, CH). ¹³C NMR (125.8 MHz, CDCl₃, 300 K) δ 16.78 (s, CH₃); 11.54 (s, SiCH). ²⁹Si NMR (99.4 MHz, CDCl₃, 300 K) δ -66.3.

Synthesis of $[((CH_3)_2CHCH_2)SiO_{1.5}]_{\Sigma_8}$: $(CH_3)_2CHCH_2SiCl_3$ (8.3 mL, 0.05 mol) was added with vigorous stirring to a mixture of CH₂Cl₂ (200 mL) and water (5 mL). The mixture was then refluxed overnight. Upon cooling, the CH₂Cl₂ layer was decanted, dried over CaCl₂ (5 g) and evaporated to afford [((CH₃)₂CHCH₂)SiO_{1.5}]_∞ resin in quantitative yield. The ²⁹Si{¹H} NMR spectrum of the resin exhibits a broad featureless resonance characteristic of silsesquioxane resins and no sharp resonances attributable to discrete polyhedral silsesquioxanes (e.g., $[(((CH_3)_2CHCH_2)SiO_{1.5})_n]_{\Sigma_n}$ with $n=6,\,8,\,10,\,12,\,14)$. Base catalyzed redistribution of [((CH₃)₂CHCH₂)SiO_{1.5}]_∞ resin was accomplished by refluxing for 48 h in methyl isobutyl ketone (25 ml) with enough C₆H₅CH₂N(CH₃)₃OH to produce a strongly basic solution (ca. 2 mL of 40% solution in MeOH). Evaporation of the solvent (25°C, 0.01 Torr)) gave a white resinous solid, which was stirred with acetone (15 mL) and filtered to afford $[(((CH_3)_2CHCH_2)SiO_{1.5})_{\Sigma_8}]$ in 30% yield (1.64 g) as a white, microcrystalline solid. Evaporation of the acetone solution gives more [i-BuSiO3/2]_∞ resin, which undergoes further base catalyzed redistribution to produce more $[(((CH_3)_2CHCH_2)SiO_{1.5})_8]_{\Sigma_8}$. The combined yield of $[(((CH_3)_2CHCH_2)SiO_{1.5})_8]_{\Sigma_8}$ after three resin redistribution reactions is typically greater than 60%. Characterization data: ¹H NMR (500.2 MHz, C₆D₆, 300 K) δ 2.09 (m, 8 H, CH); 1.08 (d, J = 6.6 Hz, 48 H, CH3); 0.84 (d, J = 7.0 Hz, 16 H, CH₂). 13 C NMR (125.8 MHz, C_6D_6 , 300 K) δ 25.6 (s, CH₃); 24.1 (s, CH); 22.7 (s, CH₂). ²⁹Si NMR (99.4 MHz, C_6D_6 , 300 K) δ -67.5.

Preparation of $[((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}$ from $[(c-C_6H_{11})SiO_{1.5}]_{\infty}$ resin was prepared in two steps from $C_6H_5SiCl_3$, In the first step, water was added to a toluene solution of phenyltrichlorosilane to produce $[C_6H_5SiO_{1.5}]_{\infty}$ resin according to the procedure reported by Brown (*J. Am. Chem. .Soc.*, (1965), 87, 4317). This $[C_6H_5SiO_{1.5}]_{\infty}$ resin (1.0 g) was then dissolved in cyclohexane (50 mL) and hydrogenated to $[(c-C_6H_{11})SiO_{1.5}]_{\infty}$ resin in a Parr minireactor (150 °C, 220 psi, 48 h) using 10% Pd/C (1.3 g) as the catalyst. Filtration to remove the catalyst and evaporation of the solvent in vacuo afforded the $[(c-C_6H_{11})SiO_{1.5}]_{\infty}$ resin as a white solid. The ¹H NMR spectrum of this resin exhibits broad featureless resonances characteristic of $c-C_6H_{11}Si$ groups and no resonances attributable to C_6H_5Si groups. The ²⁹Si{¹H} NMR spectrum exhibits a broad featureless resonance characteristic of cyclohexyl silsesquioxane resins and no sharp resonances

attributable to discrete polyhedral silsesquioxanes (e.g., $[((c-C_6H_{11})SiO_{1.5})]_{\Sigma_n}$ with n = 6, 8, 10,1 2 12; 14). Base catalyzed redistribution of $[(c-C_6H_{11})SiO_{1.5}]_{\infty}$ resin (0.5 g) was accomplished by 3 refluxing in methyl isobutyl ketone (40 ml) with 35% aqueous NEt₄OH (2 mL, 5 mmol) in 4 MIK (40 mL) for 10 h. After cooling, the solution was decanted and evaporated to dryness in 5 vacuo to afford a brownish solid. Analysis of this solid by ²⁹Si{¹H} NMR spectroscopy and 6 HPLC indicated the formation of $[((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}$ in 10-15% 7 8 yield. 9 Examples for Process II: Reactions between POSS Systems and Silsesquioxane/Siloxane 10 11 Fragments. Preparation of $[((CH_3)SiO_{1.5})_7(CH_3CH_2OOC(CH_2)_{10})SiO_{1.5})_1]_{\Sigma_8}$: One equivalent of 12 ethylundecanoate triethoxysilane and seven equivalents of methyltrimethoxy silane (1.9g) (□ 13 were added dropwise to a refluxing solution of acetone (40ml) and 1 ml of water containing 14 15 16 17 18 19 20 42 21 22 0.15 equivalents, 235.6 mg) of potassium acetate. The reaction was refluxed for 3 days cooled and the white crystalline product was collected via filtration and was washed with MeOH to remove resin. The product was characterized by MS and X-ray diffraction. A similar procedure was followed for each of the following compounds: $[((CH_3)SiO_{1.5})_6(CH_3(CH_2)_7)SiO_{1.5})_2]_{\Sigma_{8,}}[((CH_3)SiO_{1.5})_7(CH_2=CH)SiO_{1.5})_1]_{\Sigma_{8,}}$ $[((CH_3)SiO_{1.5})_4(CH_2=CH)SiO_{1.5})_4]_{\Sigma_8}, [((CH_3)SiO_{1.5})_6(CH_2=CH)SiO_{1.5})_2]_{\Sigma_8},$ $[((CH_3)SiO_{1.5})_7(H_2N(CH_2)_3)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})_7((CH_2=CH)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})_7((CH_2=CH)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})_7((CH_2=CH)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})_7((CH_2=CH)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})_7((CH_2=CH)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})_7((CH_2=CH)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})_7((CH_2=CH)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})_7((CH_2=CH)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})_1]_{\Sigma_8},\\ [((C_6H_5)SiO_{1.5})$ $[((CH_3)SiO_{1.5})_7(H_2N(CH_2)_3)SiO_{1.5})_1]_{\Sigma_8.}\\ [((c-C_5H_9)SiO_{1.5})_7((CH_3CH_2OOC(CH_2)_{10})SiO_{1.0})_1]_{\Sigma_8.}\\ [((c-C_5H_9)SiO_{1.5})_7((CH_2OOC(CH_2)_{10})SiO_{1.0})_1]_{\Sigma_8.}\\ [((c-C_5H_9)SiO_{1.5})_7((CH_2OOC(CH_2)_{10})SiO_{1.0})_1]_{\Sigma_8.}\\ [((c-C_5H_9)SiO_{1.5})_7((CH_2OOC(CH_2)_{10})SiO_{1.0})_1]_{\Sigma_8.}\\ [((c-C_5H_9)SiO_{1.5})_7((CH_2OOC(CH_2)_{10})SiO_{1.0})_1]_{\Sigma_8.}\\ [((c-C_5H_9)SiO_{1.5})_7((CH_2OOC(CH_2)_{10})SiO_{1.0})_1]_{\Sigma_8.}\\ [((c-C_5H_9)SiO_{1.5})_7((CH_2OOC(CH_2)_{10})SiO_{1.0})_1]_{\Sigma_8.}\\ [((c-C_5H_9)SiO_{1.5})_7((CH_2OOC(CH_2)_{10})SiO_{1.0})_1]_{\Sigma_8.}\\ [((c-C_5H_9)SiO_{1.0})_7((CH_2OOC(CH_2)_{10})SiO_{1.0})_1]_{\Sigma_8.}$ 22 $[((c-C_5H_9)SiO_{1.5})_7((CH_2=CH)SiO_{1.0})_1]_{\Sigma_{8.}}$ 23 24 1.23g 25 **Preparation** $[((c-C_6H_{11})SiO_{1.5})]_{\Sigma_{6.8}}$: Α charge of 26

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of [((c-C₆H₁₁)(OH)₂SiOSi(OH)₂(c-C₆H₁₁)] was added to ethanol (50ml) followed by the addition of 5meg of KHCO₃. The reaction mixture was then allowed to react during reflux for 3 hours then the mixture was made basic through the addition of Bu₄NOH and refluxed for 2 days. The reaction was then allowed to cool and neutralized with the addition of acetic acid and the volatiles removed under reduced pressure. The residue was washed with MeOH repeatedly and dried. Yield of product 93%. The product was characterized by MS and X-ray diffraction. **Preparation of** $[((c-C_6H_{11})SiO_{15})_8]_{\Sigma_8}$: Mixtures of $[((c-C_6H_{11})SiO_{15})_6]_{\Sigma_6}[((c-C_6H_{11})SiO_{15})_6]_{\Sigma_6}$ $C_6H_{11})SiO_{1.5})_6((c-C_6H_{11})(OH)SiO_{1.0})_2]_{\Sigma_8} \qquad \text{ and } \quad [((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}$ dissolved in methylisobutylketone and reacted with 20% aq. Et₄NOH under reflux for 4 days

produce nearly $[((c-C_6H_{11})SiO_{1.5})_8]_{\Sigma_8}$. Authenticity of product was verified relative to authentic sample.

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Preparation of $[((CH_3)SiO_{1.5})]_{\Sigma_8}$: A 1.22kg (7.5 mole) charge of $(CH_3Si(OCH_3)_3)$ was added to acetone (8 l) followed by the addition of 2.37 equivalents of Me₄NOH and 405 g of water. The reaction mixture was then allowed to react during reflux for 24 hours and the product was then collected by filtration. The product was washed repeatedly with MeOH and dried. Yield 466.2 g of product 93%. The product was characterized by MS and X-ray diffraction. A similar procedure can be used to prepare $[(CH_2=CH)SiO_{1.5})_8]_{\Sigma_8}$ $[(c-C_6H_{11})SiO_{1.5})_8]_{\Sigma_8}$ Modification of this procedure will afford continuous and batch-scale production.

Preparation of [(CH₃CH₂)SiO_{1.5})₈] $_{\Sigma_8}$: A similar procedure to that above for [((CH₃)SiO_{1.5})₈] $_{\Sigma_8}$ was followed in acetone to produce a [(CH₃CH₂)SiO_{1.5})] $_{\infty}$ resin which is then taken up in THF using KOH to produce [(CH₃CH₂)SiO_{1.5})₈] $_{\Sigma_8}$: ¹H NMR (500 MHz, CDCl₃): δ (ppm) 0.602 (q, J = 7.9 Hz, 16 H), 0.990 (t, J = 7.9 Hz, 24 H); ¹³C NMR (125 MHz, CDCl₃): δ (ppm) 4.06, 6.50; ²⁹Si NMR (99.4 MHz, CDCl₃): δ (ppm) -65.42. Modification of this procedure will afford continuous and batch-scale production.

Preparation of $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})_n]_{\Sigma_n} = 8, 10$. A similar procedure above for $[((CH_3)SiO_{1.5})_8]_{\Sigma_8}$ was followed using KOH to produce $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})_n]_{\Sigma_n} n = 8$, 10 in quantitative yield. ¹H NMR (500 MHz, CDCl₃): δ (ppm) 0.563 (dd, J = 8.2, 15.1 Hz, 1 H), 0.750 (dd, J = 5.6, 15.1 Hz, 1 H), 0.902 (s, 9 H), 1.003 (d, J = 6.6 Hz, 3 H), 1.125 (dd, J = 6.4, 13.9 Hz, 1 H), 1.325 (br d, J = 13.9 Hz, 1 H), 1.826 (m, 1 H); ¹³C NMR (125 MHz, CDCl₃): δ(ppm) 23.72, 24.57, 25.06, 25.31, 25.71, 25.75, 25.78, 26.98, 29.52, 30.22, 30.28, 31.22, 53.99, 54.02, 54.33; ²⁹Si NMR (99.4 MHz, -67.95 $[((CH_1)_2CH_2CHCH_3CH_2)SiO_{1.5})_{12}]_{\Sigma_{12}}$ -67.75 -69.93, CDCl₃): $\delta(ppm)$ $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})_{10}]_{\Sigma_{10},} -66.95 \ [((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})_8]_{\Sigma_8}. \ EIMS: \ m/e$ $M^{\scriptscriptstyle +}$ 1207 (100%, M^{+} $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})_{10}]_{\Sigma_{10}},$ 1039 (17%, $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})_8]_{\Sigma_8}$. Modification of this procedure will afford continuous and batch-scale production.

Preparation of [(CF₃CH₂CH₂SiO_{1.5})₈] $_{\Sigma_8}$. A similar procedure to that above for [((CH₃)SiO_{1.5})₈] $_{\Sigma_8}$ was followed using KOH and methanol as a solvent to produce the following mixture of products [(CF₃CH₂CH₂SiO_{1.5})₈] $_{\Sigma_{12}}$ 97.5%, [(CF₃CH₂CH₂SiO_{1.5})₈] $_{\Sigma_{10}}$

- 1 2.5% ¹H NMR (300 MHz, THF-d₈): δ(ppm) 0.978 (m, CH₂), 2.234 (m, CF₃CH₂); ¹³C NMR (75.5 MHz, THF-d₈): $\delta(ppm)$ 4.99 (s, CH₂), 5.42 (s, CH₂), 28.14 (q, J = 30.5 Hz, CF₃CH₂), 2 28.32 (q, J = 30.5 Hz, CF_3CH_2), 128.43 (q, J = 276 Hz, CF_3), 128.47 (q, J = 276 Hz, CF_3); ²⁹Si 3 NMR (59.6 MHz, THF-d₈): δ (ppm) -68.38 (T₁₂), -65.84 (T₁₀), -65.59 (T₁₂); ¹⁹F {¹H} NMR 4 $(376.5 \text{ MHz}, \text{THF-d}_8) \delta(\text{ppm}) - 71.67, -71.66.$ EIMS: m/e 1715 (100%, M⁺ - H₄CF₃). 5 6 Preparation of $[(CH_3(CH_2)_{16}CH_2SiO_{1.5})_n]_{\Sigma_n}$ where n = 8,10,12. A similar procedure 7 to that above for [((CH₃)SiO_{1.5})₈]_{Σ8} was followed to produce the following mixture of 8 products ¹H NMR (500 MHz, CDCl₃): δ (ppm) 0.604 (m, 2 H), 0.901 (t, J = 7.0 Hz, 3 H), 9 1.280 - 1.405 (m, 32 H); ¹³C NMR (125 MHz, CDCl₃): δ(ppm) 12.02, 14.15, 22.79, 22.89, 29.49, 29.75, 29.79, 29.85, 29.90, 32.05, 32.76; 29 Si NMR (99.4 MHz, CDCl₃): δ (ppm) -10 70.48, -68.04 $[(CH_3(CH_2)_{16}CH_2SiO_{1.5})_{12}]_{\Sigma_{12}}$, -68.22 $[(CH_3(CH_2)_{16}CH_2SiO_{1.5})_{10}]_{\Sigma_{10}}$, -66.31 11 ₽ 12 $[(CH_3(CH_2)_{16}CH_2SiO_{1.5})_8]_{\Sigma_8}$. 13 14 Preparation of $[((CH_3)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}$ (CH₃)₂CHCH₂Si(OCH₃)₃: Isobutyltrimethoxysilane (93.3 g, 523.3 mmol) was added 5 15 16 5 17 5 18 5 19 dropwise to LiOH•H₂O (10.0 g, 238.3 mmol) and water (8.0 mL, 444 mmol) in 88/12 acetone/methanol (500 mL) at reflux. The reaction mixture was heated at reflux the was acidified by quenching it into 1N HCl(aq) (500 mL) and stirring for 2h. The resulting solid was filtered and washed with CH3CN (2 x 175 mL) and air dried. The product $[((CH_3)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7} \ was \ isolated \ in \ 94\% \ yield \ at \ 98.8\%$ □ 20 purity. Note that the above procedure can be adapted to both continuous and batch 21 production methods. 22 Preparation of [(CH₃CH₂)SiO_{1.5})₄(CH₃CH₂)(OH)SiO_{1.0})₃]_{Σ7}: A similar procedure to 23 that above for $[((CH_3)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.5})_3]_{\Sigma_7}$ was followed using acetone and LiOH to produce $[(CH_3CH_2)SiO_{1.5})_4(CH_3CH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}$ as white crystalline 24
 - 9 H), 0.982 (t, J = 7.9 Hz, 9H), 6.244 (br, 3H); 13 C NMR (125 MHz, CDCl₃): δ(ppm) 3.98 (1),

solid in 40-80% yield. ¹H NMR (500 MHz, CDCl₃): δ (ppm) 0.582 (q, J = 7.9 Hz, 6 H), 0.590

(q, J = 7.9 Hz, 2 H), 0.598 (q, J = 7.9 Hz, 6 H), 0.974 (t, J = 7.9 Hz, 3 H), 0.974 (t, J = 7.9 Hz, 3 H)

- 28 4.04 (3), 4.50 (3), 6.42 (3), 6.46 (4); ²⁹Si NMR (99.4 MHz, CDCl₃): δ(ppm) -65.85 (3), -64.83
- 29 (1), -56.36 (3). MS (electrospray): m/e 617 (70%, [M+Na]+), 595 (100%, [M+H]+).
- 30 Modification of this procedure will afford continuous and batch-scale production.

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Preparation of $[((CH_3)SiO_{1.5})_7(CH_3CH_2OOC(CH_2)_{10})SiO_{1.5})_1]_{\Sigma_8}$: One equivalent of Triethoxyethylundecanoate and seven equivalents of methyltrimethoxy silane (1.9g) (were

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solid

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added dropwise to a refluxing solution of acetone (40ml) and 1 ml of water containing 0.15
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                  equivalents, 235.6 mg) of potassium acetate. The reaction was refluxed for 3 days cooled and
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                  the white crystalline product was collected via filtration and was washed with MeOH to
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                  remove resin. The product was characterized by MS and X-ray diffraction.
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                                 Preparation
                                                                                 [((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}
                                                                                                                                                                                                        [((c-
        5
                                                                    of
                  C_6H_{11})SiO<sub>1.5</sub>)<sub>6</sub>((c-C<sub>6</sub>H<sub>11</sub>)(OH)SiO<sub>1.0</sub>)<sub>1</sub>]<sub>27</sub>: 35% aqueous NEt<sub>4</sub>OH (20 µL, 0.05 mmol) is
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                  added to a THF (0.5 mL) solution of [((c-C_6H_{11})SiO_{1.5})_6((c-C_6H_{11})(OH)SiO_{1.0})_1]_{\Sigma_7} (48 mg,
        7
                  0.05 mmol) and mixed well through agitation. After 1.5 h at 25 °C, several drops of C<sub>6</sub>D<sub>6</sub>
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                  were added and <sup>29</sup>Si{<sup>1</sup>H} NMR spectrum was recorded. The spectrum matched the data for
                  the previously reported for basic solutions of [((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}.
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                                                                                 [((c-C_6H_{11})SiO_{1.5})_2((c-C_6H_{11})(OH)SiO_{1.0})_4]_{\Sigma_6}
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                                 Preparation
                                                                                                                                        C_2-symmetry-[((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5((c-C_6H_{11})SiO_{1.5})_5
                  C_6H_{11})SiO<sub>1.5</sub>)<sub>4</sub>((c-C<sub>6</sub>H<sub>11</sub>)(OH)SiO<sub>1.0</sub>)<sub>2</sub>]<sub>\Sigma_6</sub>:
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                  C_6H_{11})(OH)SiO<sub>1.0</sub>)<sub>2</sub>]<sub>26</sub> (38 mg, 0.05 mmol) was reacted with 35% aqueous NEt<sub>4</sub>OH (20 \muL,
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                  0.05 mmol) in THF (0.5 mL) and after 30 minutes at 25 °C, several drops of C<sub>6</sub>D<sub>6</sub> were
                  added and <sup>29</sup>Si{<sup>1</sup>H} NMR spectrum was recorded. The spectrum matched the spectrum of
                  authentic [((c-C_6H_{11})SiO_{1.5})_2((c-C_6H_{11})(OH)SiO_{1.0})_4]_{\Sigma_6} prepared by the reaction of [((c-C_6H_{11})SiO_{1.5})_2((c-C_6H_{11})(OH)SiO_{1.0})_4]_{\Sigma_6}
                  C_6H_{11})SiO<sub>1.5</sub>)<sub>6</sub>]\Sigma_6 with aqueous NEt<sub>4</sub>OH.
     17
                                                                         [((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}
                                                                                                                                                                                from
                                                                                                                                                                                                        [((c-
     18
                                 Preparation
      19
                  C_6H_{11})SiO_{1.5}_{0}((c-C_6H_{11})(OH)SiO_{1.0})_1]_{\Sigma_7}:
                                                                                                                    Α
                                                                                                                                solution
                                                                                                                                                        of
                                                                                                                                                                    [((c-C_6H_{11})SiO_{15})_6((c-C_6H_{11})SiO_{15})_6]
     20
                  C_6H_{11}(OH)SiO_{10}]<sub>27</sub> (0.46 mmol) and 35% aqueous NEt<sub>4</sub>OH (0.2 mL, 0.49 mmol) was
                  refluxed in THF (5 mL) for 5 h then neutralized with dilute aqueous HCl. Evaporation of the
     21
     22
                  volatiles afforded a white solid, which was dissolved in Et<sub>2</sub>O and dried over anhydrous
                  MgSO<sub>4</sub>. Filtration and evaporation of the solvent afforded a white microcrystalline solid in
     23
                                              Analysis of the product mixture by <sup>29</sup>Si NMR spectroscopy indicated that the
     24
                  high yield.
                  major product was [((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}; small amounts of [((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}
     25
     26
                  C_6H_{11})SiO<sub>1.5</sub>)<sub>8</sub>]<sub>\Sigma_8</sub> were also present.
                                  Preparation \quad of \quad [((c-C_5H_9)SiO_{1.5})_8((CH_3)_2SiO_{1.0})_1]_{\Sigma_9} \quad from \quad [((c-C_5H_9)SiO_{1.5})_8]_{\Sigma_8} : \\
     27
     28
                  Reaction of [((c-C_5H_9)SiO_{1.5})_8]_{\Sigma_8} (2.21 g, 2.28 mmol) and octamethyltetracyclosiloxane
                  (1.35 g, 4.56 mmol) in 2 mL toluene with Me<sub>4</sub>NOH (9.4 mg of 25% solution in MeOH,
     29
                  0.626 mmol) is allowed for 24 h at 120 °C. The mixture is then quenched with 6 N
     30
```

HCl (1 mL), extracted with Et₂O (3 mL), evaporated to dryness to give a white pasty

of

70%

 $[((c-C_5H_9)SiO_{1.5})_8((CH_3)_2SiO_{1.0})_1]_{\Sigma_9}$

which contains a mixture

```
polydimethylsiloxane, and 29% [((c-C<sub>5</sub>H<sub>9</sub>)SiO<sub>1.5</sub>)<sub>8</sub>]\Sigma_8. Analysis by <sup>29</sup>Si{<sup>1</sup>H} NMR
    1
         (CDCl<sub>3</sub>) spectroscopy revealed [((c-C_5H_9)SiO_{1.5})_8((CH_3)_2SiO_{1.0})_1]_{\Sigma_9} at (\delta -65.76, -68.30, -
    2
    3
         68.34, 2:2:4).
                 Preparation of [((CH_3)_2CHCH_2)SiO_{1.5})_8((5-norbornene-2-ethyl)(CH_3))SiO_{1.5})_1]_{\Sigma_9}
    4
         from [((CH_3)_2CHCH_2)SiO_{1.5})_6((CH_3)_2CHCH_2)(OH)SiO_{1.0})_2]_{\Sigma_8}. An Et<sub>2</sub>O (5 mL) solution of
    5
         [((CH_3)_2CHCH_2)SiO_{1.5})_6((CH_3)_2CHCH_2)(OH)SiO_{1.0})_2]_{\Sigma_8} (890 mg, 1.00 mmol) was added a
    6
         mixture of dichloromethyl(5-norbornene-2-ethyl)silane (endo/exo = 3/1, 282.3 mg, 1.20
    7
         mmol), Et<sub>3</sub>N (195 µL, 1.4 mmol), and Et<sub>2</sub>O (5 mL) at -35 °C. After addition the resulting
    8
         mixture was warmed to room temperature and stirred for 20 h. The mixture was hydrolyzed
    9
         and extracted with diethyl ether, washed with brine, and dried over Na<sub>2</sub>SO<sub>4</sub>. Evaporation of
   10
         the volatiles gave [((CH_3)_2CHCH_2)SiO_{1.5})_8((5-norbornene-2-ethyl)(CH_3))SiO_{1.5})_1]_{\Sigma_9} (720 mg,
   11
         0.68 mmol) as a white powder in 68% yield. <sup>1</sup>H NMR (CDCl<sub>3</sub>) δ 0.10 (s, 9H), 0.12 (s, 3H),
□ 12
12
13
14
15
16
         0.48-0.68 (m, 72H), 0.84-1.05 (m, 194H), 1.06-1.36 (m, 18H), 1.40-1.50 (m, 4H), 1.80-1.94
         (m, 32H), 1.95-2.03 (m, 3H), 2.55 (br s, 1H), 2.77 (br s, 3H), 2.78-2.83 (m, 4H), 5.93 (q, ^{3}J =
         5 Hz, {}^{3}J = 10 Hz, 3H), 6.04 (q, {}^{3}J = 5 Hz, {}^{3}J = 10 Hz, 1H), 6.09-6.14 (m, 4H). {}^{13}C NMR
         (CDCl_3) \delta -1.11, 15.86, 16.21, 22.58, 23.20, 23.83, 23.98, 24.06, 24.18, 25.76, 25.81, 25.89,
17
C 18
C 19
C 20
C 21
         27.71, 29.50, 32.41, 33.10, 41.89, 41.97, 42.09, 42.65, 45.10, 45.20, 46.03, 49.61, 132.35,
         136.29, 136.87, 136.96. <sup>29</sup>Si NMR (CDCl<sub>3</sub>) \delta -69.25, -69.23, -69.21, -69.15, -67.04, -
         21.73, -21.63.
                 Preparation [((CH_3)SiO_{1.5})_7(CH_2=CCH_3(O)CO(CH_2)_3)SiO_{1.5})_1]_{\Sigma_8}: An Et<sub>2</sub>O (80)
         mL) solution of Methacryloxypropyltrichlorosilane (0.69 mL, 3.31 mmol) and 1,8-
  21
         bis(dimethylamino)naphthalene (2.34 g, 10.91 mmol) was added to an Et<sub>2</sub>O (20 mL)
   22
         solution of [((CH_3)SiO_{1.5})_4((CH_3)(OH)SiO_{1.0})_3]_{\Sigma_7} (1.26 g, 2.54 mmol) at -35 °C. The
   23
         mixture was further stirred at room temperature for 5 h and then concentrated
   24
         under reduced pressure. The residue was extracted with ether. The insoluble
   25
         materials were filtered. The filtrate was concentrated to give an oil-like solid. The
   26
         solid was passed through a silica gel column using hexane/Et<sub>2</sub>O (50:1) as an eluent.
   27
          Evaporation of the volatiles gave [((CH_3)SiO_{1.5})_7(CH_2=CCH_3(O)CO(CH_2)_3)SiO_{1.5})_1]_{\Sigma_8}
   28
          (415 mg, 0.64 mmol) as a white solid in 25% yield. <sup>1</sup>H NMR (CDCl<sub>3</sub>) δ 0.136 (s, 3H),
   29
          0.142 (s, 12H), 0.146 (s, 6H), 0.64-0.72 (m, 2H), 1.72-1.82 (m, 2H), 1.94 (s, 3H), 4.11 (t, J
   30
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= 6.78 Hz, 3H), 5.54 (t, J = 1.58 Hz, 1H), 6.10 (br s, 1H). ¹³C NMR (CDCl₃) δ -4.56, -

4.48, 8.24, 18.31, 22.19, 66.46, 125.16, 136.53, 167.46. ²⁹Si NMR (CDCl₃) δ -67.71, -1 66.00,-65.69. Calcd for C₁₄H₃₂O₁₄Si₈: C, 25.91; H, 4.97. Found: C, 25.69; H, 4.99. 2 Preparation of $[((CH_3C_6H_4SiO_{1.5})_8((CH_2=CCH_3)(O)CO(CH_2)_3)(H_3C)SiO_{1.0})_1]_{\Sigma_9}$: An 3 of of mixture 4 Et₂O (20)solution $[((CH_3C_6H_5)SiO_{1.5})_6((CH_3C_6H_5)(OH)SiO_{1.0})_2]_{\Sigma_8}/[((CH_3C_6H_5)SiO_{1.5})_8]_{\Sigma_8} \ (581.9 \ mg, \ 4/1, \ 0.40)_2/(CH_3C_6H_5)SiO_{1.5})_8/(CH_3C_6H_5)(OH)SiO_{1.0})_2/(CH_5C_6H_5)(OH)SiO_{1.0})_2/(CH_5C_6H_5)(OH)SiO_{1.0})_2/(CH_5C_6H_5)(OH)SiO_{1.0})_2/(CH_5C_6H_5)(OH)SiO_{1.0})_2/(CH_5$ 5 mmol) was added a mixture of dichloromethacryloxypropylmethylsilane (108.8 μ L, 6 0.50 mmol), Et₃N (139.4 μ L, 1.00 mmol), and Et₂O (3 mL) at room temperature and 7 stirred for 20 h, was then hydrolyzed, and extracted with diethyl ether. The extract 8 was washed with brine, dried over Na₂SO₄ and after evaporation of the volatiles 9 gave $[((CH_3C_6H_4SiO_{16})_8((CH_2=CCH_3)(O)CO(CH_2)_3)(H_3C)SiO_{10})_1]_{\Sigma_9}$ (475.5 mg, 0.36 mmol) 10 as a white solid in 89% yield. ¹H NMR (CDCl₃) δ 0.43 (s, 3H), 0.85-0.90 (m, 2H), 1.87-11 12 7 13 14 15 1.95 (m, 2H), 1.95 (s, 3H), 2.42 (s, 6H), 2.43 (s, 12H), 2.44 (s, 6H), 4.16 (t, $^{3}J = 6.8 \text{ Hz}$, 2H), 5.56 (br s, 1H), 6.11 (br s, 1H), 7.19-7.29 (m, 18H), 7.59-7.68 (m, 10H), 7.71-7.79 $(m,\,4H).\ \ ^{13}C\ NMR\ (CDCl_3)\ \delta\ -0.92,\,12.87,\,18.24,\,21.57,\,22.12,\,127.14,\,127.38,\,127.43,$ 128.49, 128.55, 128.58, 128.64,133.94, 134.16, 134.19, 134.25, 140.23, 140.39, 140.59, 16 17 17 18 19 167.37. ²⁹Si NMR (CDCl₃) δ –78.72, –78.51,–76.98, –18.75. Preparation of [((CH₃C₆H₄SiO_{1.5})₇((CH=CH₂)(CH₃)₂SiO_{1.0})₃] Σ_7 : A THF (15 mL) solution of [((CH₃C₆H₅)SiO_{1.5})₈] Σ_8 (572.9 mg, 0.50 mmol) was added an aqueous solution of Et₄NOH (35%, 226.2 μL, 0.55 mmol) at room temperature. After addition the resulting mixture was stirred at the same temperature for 6 h. The mixture was 20 neutralized with 1N HCl solution and extracted with diethyl ether. The organic 21 layer was washed with brine, dried over MgSO4 and volatiles evaporated to give 22 The $[((CH_3C_6H_5)SiO_{15})_4]$ 23 $[((CH_3C_6H_5)SiO_{1.5})_4((CH_3C_6H_5)(OH)SiO_{1.0})_3]_{\Sigma_7}.$ $((CH_3C_6H_5)(OH)SiO_{1.0})_3]_{\Sigma7}$ was dissolved in an Et₂O (30 mL) and a mixture of 24 chlorodimethylvinylsilane (505 μ L, 3.66 mmol), Et₃N (595 μ L, 4.27 mmol), and Et₂O 25 (3 mL) was added at room temperature and stirred for 7 h. The mixture was 26 hydrolyzed and extracted with diethyl ether washed with brine, dried over MgSO4, 27 and evaporated to give a solid. Recrystallization of the solid from hexane afforded 28 colorless crystals of $[((CH_3C_6H_4SiO_{15})_4((CH_3C_6H_5)(OSi(CH_3)_2(CH=CH_2))SiO_{10})_3]_{\Sigma_7}$ (230) 29

mg, 0.18 mmol) in 36% yield. ¹H NMR (CDCl₃) δ 0.38 (s, 18H), 2.33 (s, 9H), 2.34 (s,

1 9H), 2.39 (s, 3H), 5.90 (dd, ${}^{2}J = 20.4 \text{ Hz}$, ${}^{3}J = 3.8 \text{ Hz}$, 3H), 6.03 (dd, ${}^{3}J = 14.9 \text{ Hz}$, ${}^{3}J = 3.8 \text{ Hz}$ Hz, 3H), 6.28 (dd, ${}^{2}J$ = 20.4 Hz, ${}^{3}J$ = 3.8 Hz, 3H), 7.01 (d, ${}^{3}J$ = 7.7 Hz, 12H), 7.19 (d, ${}^{3}J$ = 2 3 7.7 Hz, 2H), 7.27 (d, ${}^{3}I = 7.7$ Hz, 6H), 7.41 (d, ${}^{3}I = 7.7$ Hz, 6H), 7.53 (d, ${}^{3}I = 7.7$ Hz, 2H). ¹³C NMR (CDCl₃) δ 0.42, 21.51, 21.54, 21.60, 127.51, 127.97, 128.14, 128.26, 128.55, 4 5 129.51,132.26, 134.06, 134.11, 134.17, 138.78, 139.65, 139.77, 140.37. ²⁹Si NMR (CDCl₃) 6 δ -77.81, -77.29, -77.15, -0.50. 7 Preparation $[(((CH_3)_3SiO)SiO_{1.5})_6]_{\Sigma_6}$ from $[(((CH_3CH_2)_4NO)SiO_{1.5})_6]_{\Sigma_6}$: To a 8 solution of trimethylchlorosilane (140.0 mL, 1.10 mol), heptane (500 mL), and N,N-9 dimethylformamide (200 mL) was added a powder of [(((CH₃CH₂)₄NO)SiO_{1.5})₆]_{Σ6} (11.9 g, 10.0 mmol) over a period of ca. 30 min at 0 °C. 10 After addition of all the 11 $[(((CH_3CH_2)_4NO)SiO_{1.5})_6]_{\Sigma_6}$ the mixture was stirred for an additional 30 min then allowed to □12 warm to room temperature overnight. An ice-water (1 L) was added and the mixture stirred 回13 回14 回15 回16 for 30 min. The organic layer was washed with water until neutral, dried over MgSO₄, and concentrated. To the residue was added a methanol and the soluble part was removed by filtration to leave a pure $[(((CH_3)_3SiO)SiO_{1.5})_6]_{\Sigma_6}$ (4.1 g, 4.84 mmol) as a white solid in 48% yield: ¹H NMR (CDCl₃) δ 0.17 (s, 54H). ¹³C NMR (CDCl₃) δ 1.18. ²⁹Si NMR (CDCl₃) δ 17 0 18 0 19 0 20 14.27, -99.31. Preparation of $[(((CH_3)_3SiO)SiO_{1.5})_6((CH_2=CH)(CH_3)_2SiO_{1.0})_4]_{\Sigma_6}$: To an Et₂O (5 mL) solution of vinyldimethylchlorosilane (121.5 μL, 0.88 mmol) and NEt₃ (139.4 μL, 1.00 mmol) was added an Et₂O solution of $[(((CH_3)_3SiO)SiO_{1.5})_2(((CH_3)_3SiO)(OH)SiO_{1.0})_4]_{\Sigma_6}$ 21 (174.7 mg, 0.20 mmol) at room temperature. The mixture was stirred at room temperature 22 for 4h and then concentrated under reduced pressure. The residue was extracted with hexane. 23 The insoluble materials were filtered. The filtrate was concentrated to give a spectroscopic 24 pure $[(((CH_3)_3SiO)SiO_{1.5})_6((CH_2=CH)(CH_3)_2SiO_{1.0})_4]_{\Sigma_6}$ (225.6 mg, 0.18 mmol) as a white 25 foam solid in 92% yield: ¹H NMR (CDCl₃) δ 0.13 (s, 54H), 0.14 (s, 12H), 0.18(s, 12H), 5.73 26 (d, J = 4.0 Hz, 2H), 5.77 (d, J = 4.0 Hz, 2H), 5.91 (d, J = 4.0 Hz, 2H), 5.94 (d, J = 4.0 Hz, 2H)27 2H), 6.11 (d, J = 15.0 Hz, 2H), 6.15 (d, J = 15.0 Hz, 2H). ¹³C NMR (CDCl₃) δ 0.11, 1.52, 28 1.62, 132.00, 138.79. ²⁹Si NMR (CDCl₃) δ 11.24, 10.17, -1.35, -108.31, -108.70. MS (ESI): 29 Calcd for C₃₄H₉₀O₁₇Si₁₆Na, 1243.2. Found: 1243.6. 30 of $[(((CH_3)_3SiO)SiO_{1.5})_6((C_6H_5)SiO_{1.5})_1((CH_2=CCH_3)(O)CO)]$ Preparation

(OH)SiO₁₀), ₂₇: An Et₂O (8 mL) solution of methacryloxypropyltrichlorosilane (340.3

31

32

 $(CH_2)_3SiO_{1.5})_1]_{\Sigma_8}$

from

 $[(((CH_3)_3SiO)SiO_{1.5})_4((C_6H_5)(OH)SiO_{1.0})_1(((CH_3)_3SiO)$

```
1
                          \muL, 1.63 mmol) and NEt<sub>3</sub> (748.5 \muL, 5.37 mmol) was added to an Et<sub>2</sub>O (7 mL) solution
                          of [(((CH_3)_3SiO)SiO_{1.5})_4((C_6H_5)(OH)SiO_{1.0})_1(((CH_3)_3SiO)(OH)SiO_{1.0})_2]_{\Sigma_7} (817.0 mg, 0.81)
             2
                          mmol) at -35 °C and the mixture was stirred at room temperature for 6 h and then
             3
             4
                          concentrated under reduced pressure. The residue was extracted with hexane,
                         insoluble materials were filtered, and the filtrate was concentrated to give an oil.
             5
            6
                         The oil was purified using a silica gel column and hexane/Et<sub>2</sub>O (50:1) as an eluent.
            7
                         Evaporation
                                                                           of
                                                                                               the
                                                                                                                     volatiles
                                                                                                                                                           gave
                                                                                                                                                                                      [(((CH_3)_3SiO)SiO_{1.5})_6((C_6H_5)SiO_{1.5})_1]
                         ((CH_2=CCH_3)(O)CO(CH_2)_3SiO_{1.5})_1]_{\Sigma_8} (210.0 mg, 0.18 mmol) as a white solid in 25%
            8
                         yield. <sup>1</sup>H NMR (CDCl<sub>3</sub>) δ 0.13 (s, 18H), 0.16 (s, 18H), 0.17 (s, 9H), 0.18 (s, 9H), 0.73-
            9
         10
                         0.80 \text{ (m, 2H)}, 1.77-1.85 \text{ (m, 2H)}, 1.93 \text{ (s, 3H)}, 4.11 \text{ (t, } J = 6.62 \text{ Hz, 2H)}, 5.54 \text{ (t, } J = 1.58 \text{ (s, 3H)}, 1.77-1.85 \text{ (m, 2H)}, 1.93 \text{ (s, 3H)}, 4.11 \text{ (t, } J = 6.62 \text{ Hz, 2H)}, 5.54 \text{ (t, } J = 1.58 \text{ (s, 3H)}, 1.93 \text{ (s, 3H)}, 
         11
                         Hz, 1H), 6.09 (br s, 1H), 7.35-7.41 (m, 2H), 7.43-7.48 (m, 1H), 7.66-7.72 (m, 2H). <sup>13</sup>C
 12
13
13
                         NMR (CDCl<sub>3</sub>) 8 1.24, 7.95, 18.30, 22.11, 66.39, 125.22, 127.70, 130.22, 130.69, 134.08,
                         136.41, 167.37. <sup>29</sup>Si NMR (CDCl<sub>3</sub>) δ -109.06, -108.88, -108.82, -78.86, -65.60, 12.55,
12.58, 12.59. Calcd for C<sub>31</sub>H<sub>70</sub>O<sub>20</sub>Si<sub>14</sub>: C, 32.21; H, 6.10. Found: C, 31.99; H, 6.35. MS
                         (ESI) Calcd for 1177.1 [M + Na]+, 1193.1 [M + K]+. Found: 1177.2 [M + Na]+, 100%;
                        1193.2 [M+K]+, 10%.
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Examples for Process III: Selective Opening, Functionalization and Rearrangement of **POSS Nanostructures**

Preparation of $[((CH_2=CH)SiO_{1.5})_6((CH_2=CH)(HO)SiO_{1.0})_2]_{\Sigma_8}$ from [((CH₂=CH)SiO_{1.5})₈]_{Σ 8}: An aqueous solution of NEt₄OH (33%, 2 mL, 0.25 mmol) in THF 21 (10 mL, -35 °C) was added to a stirred solution of [((CH₂=CH)SiO_{1.5})₈] Σ_8 (2.95 g, 4.66 mmol) 22 23 in 1:1:1 THF/CH₂Cl₂/isopropanol (300 mL), which was chilled in a 24 methanol/water and N₂) cold bath. After 4.3 hours the reaction was quenched with 1M HCl 25 (20 mL, -35 °C) and the solution was washed with 1M HCl (2 x 40 mL), water (2 x 40 mL), 26 and sat. aq. NaCl solution (40 mL). After drying over Na₂SO₄, and removal of the solvent in vacuo (25 °C, 0.01 Torr) a white solid (3.01 g, 99%) was isolated. The product 27 28 $[((CH_2=CH)SiO_{1.5})_6((CH_2=CH)(HO)SiO_{1.0})_2]_{\Sigma_8}$ prepared by this procedure is 29 spectroscopically pure. Additional purification can be accomplished through recrystallization from CH₂Cl₂/hexanes/acetic acid (25 °C). ¹H NMR (CDCl₃, 500.2 MHz, 25 °C): δ 6.12-30 5.74 (m, SiCH=CH₂), 5.7 (br, SiOH). ¹³C{¹H} NMR (CDCl₃, 125.7 MHz, 25 °C): δ 137.00, 31 32 136.87, 136.81 (s, CH₂, rel. int. 1:1:2), 129.75, 129.17, 128.80 (s, SiCH, rel. int. 1:2:1).

```
1
            <sup>29</sup>Si{<sup>1</sup>H} NMR (CDCl<sub>3</sub>, 99.4 MHz, 25 °C): \delta -71.39 (s, SiOH), -79.25, -80.56 (s, SiCH, rel.
            int. 1:2). Mass Spectrum (ESI) m/z calcd for C_{16}H_{26}O_{13}Si_8: [M + H]^+ 650.96, found 651.2
     2
            (20%); [M + Na]<sup>+</sup> 672.94, found 673.1 (100%). Mass Spectrum (EI) m/z calculated for
     3
     4
            C_{16}H_{26}O_{13}Si_8: [M]<sup>+</sup> 649.9528, found 649.9532 (4%); [M - C_2H_3]<sup>+</sup> 622.9, found 623.2 (100%).
     5
                     Preparation
                                                of
                                                           [((Boc-NHCH,CH,CH,)SiO<sub>1.5</sub>)<sub>6</sub>((Boc-NHCH,CH,CH,)
     6
                                    from
                                               [((Boc-NHCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>)SiO<sub>1.5</sub>)<sub>8</sub>]\Sigma_8: A solution of [((Boc-
           (HO)SiO_{1,0})_2]_{\Sigma_8}
     7
           NHCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>)SiO<sub>1.5</sub>)<sub>8</sub>]\Sigma_8 (0.11 mmol) in 1:1:1 CH<sub>2</sub>Cl<sub>2</sub>/THF/isopropanol (-35 °C, 7.5 mL)
     8
           and aq. NEt<sub>4</sub>OH (35 wt%, 50 µL, 0.13 mmol) was stirred at -35 °C for 2 h. Addition of
     9
           CH<sub>3</sub>CO<sub>2</sub>H (0.1 mL, -35 °C), extraction with a saturated aqueous NaCl solution (3 x 10 mL),
   10
           drying over Na<sub>2</sub>SO<sub>4</sub>, and removal of the solvent in vacuo (25 °C, 0.001 Torr) afforded [((Boc-
   11
           NHCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>)SiO<sub>1.5</sub>)<sub>6</sub>((Boc-NHCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>)(HO)SiO<sub>1.0</sub>)<sub>2</sub>]<sub>Σ8</sub> as a colorless paste in a 63 %
   12
           yield. <sup>29</sup>Si{<sup>1</sup>H} NMR (CDCl<sub>3</sub>, 99.4 MHz, 25 °C): δ -57.798, -65.674, -67.419 (s, rel. int.
□13
           1:1:2). Mass Spectrum (ESI) m/z calcd for C_{64}H_{130}N_8O_{29}Si_8: [M + Na]^+ 1721.7, found
14
15
16
           1722.1.
                     Preparation of [((Cbz-Pro-NHCH,CH,CH,CH,)SiO<sub>1.5</sub>)<sub>6</sub>((Cbz-Pro-NHCH,CH,CH,))
           (HO)SiO_{1,0})_2|_{\Sigma_8} from [((Cbz-Pro-NHCH_2CH_2CH_2)SiO_{1,5})_8]_{\Sigma_8}: A solution of [((Cbz-Pro-NHCH_2CH_2CH_2)SiO_{1,5})_8]_{\Sigma_8}:
17 18 18
           NHCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>)SiO<sub>1.5</sub>)<sub>8</sub>]<sub>8</sub> (0.11 mmol) in 1:1:1 CH<sub>2</sub>Cl<sub>2</sub>/THF/isopropanol (-35 °C, 7.5 mL)
           and aq. NEt<sub>4</sub>OH (35 wt%, 50 μL, 0.13 mmol) was stirred at -35 °C for 2 h. Addition of
□ 19
□ 20
□ 21
□ 21
           CH<sub>3</sub>CO<sub>2</sub>H (0.1 mL, -35 °C), extraction with a saturated aqueous NaCl solution (3 x 10 mL),
           drying over Na<sub>2</sub>SO<sub>4</sub>, and removal of the solvent in vacuo (25 °C, 0.001 Torr) afforded [((Cbz-
           Pro-NHCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>)SiO<sub>1.5</sub>)<sub>6</sub>((Cbz-Pro-NHCH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>)(HO)SiO<sub>1.0</sub>)<sub>2</sub>]\Sigma_8 as a colorless paste in
□ 22
           77 % yield. <sup>29</sup>Si{<sup>1</sup>H} NMR (CDCl<sub>3</sub>, 99.4 MHz, 25 °C): δ -58.4, -65.543, -67.470 (s, rel. int.
   23
           1:1:2). Mass Spectrum (ESI) m/z calcd for C_{128}H_{170}N_{16}O_{37}Si_8: [M + Na]^+ 2772.54, found
   24
           2772.9.
   25
                     26
           CH_2CH_2)(HO)SiO_{1.0}_{2}]_{\Sigma_8} from [((MeO_2CCH_2CMe_2CH_2CH_2CH_2CH_2)SiO_{1.5})_8]_{\Sigma_8}: A solution of
   27
           [((MeO_2CCH_2CMe_2CH_2CH_2CH_2)SiO_{1.5})_8]_{\Sigma_8} (0.11 mmol) in 1:1:1 CH<sub>2</sub>Cl<sub>2</sub>/THF/isopropanol (-
   28
           35 °C, 7.5 mL) and aq. NEt<sub>4</sub>OH (35 wt%, 50 \muL, 0.13 mmol) was stirred at -35 °C for 2 h.
   29
           Addition of CH<sub>3</sub>CO<sub>2</sub>H (0.1 mL, -35 °C), extraction with a saturated aqueous NaCl solution (3
   30
           x 10 mL), drying over Na<sub>2</sub>SO<sub>4</sub>, and removal of the solvent in vacuo (25 °C, 0.001 Torr)
   31
           afforded
                               [((MeO<sub>2</sub>CCH<sub>2</sub>CMe<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>)SiO<sub>1.5</sub>)<sub>6</sub>((MeO<sub>2</sub>CCH<sub>2</sub>CMe<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>CH<sub>2</sub>)(HO)
   32
           SiO_{1.0}<sub>2</sub>]<sub>\Sigma_8</sub> as a colorless paste in 66 % yield. <sup>29</sup>Si(<sup>1</sup>H) NMR (CDCl<sub>3</sub>, 99.4 MHz, 25 °C): \delta -
   33
           57.551, -64.981, -66.841 (s, rel. int. 1:1:2). Mass Spectrum (ESI) m/z calculated for
   34
           C_{64}H_{122}O_{29}Si_8: [M + Na]<sup>+</sup> 1601.61, found 1602.0.
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1
                  Preparation of [(((CH_3)_3SiO)SiO_{1.5})_2(((CH_3)_3SiO)(OH)SiO_{1.0})_4]_{\Sigma_6}: To a THF (4 mL)
    2
          solution of [(((CH_3)_3SiO)SiO_{1.5})_6]_{\Sigma_6} (169.5 mg, 0.20 mmol) was added an aqueous solution
         of NEt<sub>4</sub>OH (35%, 82.3 μL, 0.20 mmol) at -40 °C. The resulting mixture was stirred between
    3
    4
         -40 to -25 °C for 40 min. The mixture was neutralized with aqueous solution of HCl (1N, 3
         mL) and extracted with diethyl ether. The organic layer was washed with brine, dried over
    5
    6
         MgSO<sub>4</sub>,
                         and
                                     evaporated
                                                        to
                                                                 give
                                                                             a
                                                                                     spectroscopic
                                                                                                            pure
    7
         [(((CH_3)_3SiO)SiO_{1.5})_2(((CH_3)_3SiO)(OH)SiO_{1.0})_4]_{\Sigma_6} (174.7 mg, 0.20 mmol) as a white wax solid
    8
         in 99% yield. <sup>1</sup>H NMR (CDCl<sub>3</sub>) δ 0.14 (s, 54H). <sup>13</sup>C NMR (CDCl<sub>3</sub>) δ 1.24, 1.28. <sup>29</sup>Si NMR
    9
         (CDCl_3) \delta 12.44, 12.19, -100.12, -109.27.
  10
                  Preparation
                                   of
                                             [(((H_3C)_3SiO)SiO_{1.5})_6(((H_3C)_3SiO)(OH)SiO_{1.0})_2(((CH_2=CH)))]
  11
         (OH)SiO_{1.0}<sub>1,0</sub><sub>1,0</sub><sub>1,0</sub><sub>1,5</sub>. The starting polyhedral oligomeric silicate [(((H_3C)_3SiO)SiO_{1.5})_6] was
<sub>=</sub>12
         prepared via a procedure analogous to that published by Harrison et al. Main Group Metals
13
         Chemistry (1997) vol 20, pp. 137-141. A solution of Vinyltrimethoxysilane (0.04 mL, 0.26
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         mmol) and aqueous NEt<sub>4</sub>OH (0.1 mL, 0.25 mmol) was prereacted for 10 minutes and then
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         added to a solution of [(((H_3C)_3SiO)SiO_{1.5})_6]_{\Sigma_6} (198 mg, 0.23 mmol) and was stirred for 15
         minutes at room temperature. The reaction was then neutralized through the addition of
<sup>™</sup>17
         dilute HCl and the solvent was removed under reduced pressure. The residue was then taken
<u>ا</u> 18
         up in diethylether filtered and dried over anhydrous MgSO<sub>4</sub>. Filtration and evaporation of the
型19
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         solvent afforded a yellow oil (2.31 mg, 0.002mol) in 10.2% yield. Selected characterization
         data: ^{29}Si\{^{1}H\} NMR (99.3 MHz, CDCl_{3}, 25 °C) \delta -99.8, -100.1, -108.0, -108.9. MS (ESI,
= 21
         100\% MeOH): m/e 977.1 ({M + Na}]^{+}.
  22
                 Preparation
                                       of
                                                [((CH_3CH_2)SiO_{1.5})_6((CH_3CH_2)(HO)SiO_{1.0})_2]_{\Sigma_8}
                                                                                                          from
  23
         [((CH_3CH_2)SiO_{1.5})_8]_{\Sigma_8}:
                                      Α
                                            CH<sub>2</sub>Cl<sub>2</sub>/i-PrOH/THF(10/10/10
                                                                                       mL)
                                                                                                solution
                                                                                                              of
  24
         [((CH_3CH_2)SiO_{1.5})_8]_{\Sigma_8} (259.7 mg, 0.40 mmol) was added an aqueous solution of
         Et<sub>4</sub>NOH (35%, 493.5 μL, 1.20 mmol) at -20 °C. After addition the resulting mixture
  25
  26
         was stirred at the same temperature for 7 h. The mixture was neutralized with 1N
  27
         HCl solution and extracted with diethyl ether. The organic layer was washed with
  28
         brine, dried over Na<sub>2</sub>SO<sub>4</sub>. Evaporation of the volatiles gave spectroscopically pure
  29
         [((CH_3CH_2)SiO_{1.5})_6((CH_3CH_2)(HO)SiO_{1.0})_2]_{\Sigma_8} (263.5 mg, 0.39 mmol) as a white solid in
  30
         99% yield. <sup>1</sup>H NMR (CDCl<sub>3</sub>) δ 0.54-0.66 (m, 16H), 0.93-1.04 (m, 24H), 5.21 (br s, 2H).
  31
         <sup>13</sup>C NMR (CDCl<sub>3</sub>) δ 3.94, 4.36, 4.41, 6.42, 6.46, 6.50. <sup>29</sup>Si NMR (CDCl<sub>3</sub>) δ -66.73, -
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64.95,-57.63. Calcd for C₁₆H₄₂O₁₃Si₈: C, 28.80; H, 6.35. Found: C, 28.78; H, 6.43.

from of $[(((CH_3)_2CH)SiO_{1.5})_6(((CH_3)_2CH)(HO)SiO_{1.0})_2]_{\Sigma_8}$ 1 Preparation $[(((CH_3)_2CH)SiO_{1.5})_8]_{\Sigma_8}$: $[(((CH_3)_2CH)SiO_{1.5})_8]_{\Sigma_8}$ (302 mg, 0.397 mmol) was dissolved in 2 15mL of solvents' mixture (iso-propanol:CH₂Cl₂:THF = 1:1:1). The aqueous 35% solution of 3 EtN₂OH (0.8 mL) was added to the solution of $[(((CH_3)_2CH)SiO_{1.5})_8]_{\Sigma_8}$ at -12°C. After 7 4 hours, the reaction mixture was decanted, extracted with Et₂O (4 x 3 mL). The extract was 5 dried over anhydrous Na2SO4, then evaporated in vacuo, obtained a yellow solid which was 6 purified by column chromatography (SiO₂, 60%CH₂Cl₂ in hexanes) to afford a 7 spectroscopically pure powder (189 mg, 61%). ¹H NMR (500 MHz, CDCl₃, 25 °C): δ 3.90 8 (br s, SiOH, 2H), 1.03 (br m's, 48H), 0.91 (br m's, 8H. ¹³C{¹H} NMR (125 MHz, CDCl₃, 25 9 °C): δ 16.91, 16.79, 16.64 (8:4:4 for CH₃), 11.91, 11.77, 11.38 (4:2:2 for CH), ²⁹Si{¹H} NMR 10 (99 MHz, CDCl₃, 25 °C): δ -57.92, -65.29, -67.70 (2:2:4). IR (25 °C, KBr, cm⁻¹): 3352, 2950, 11 2869, 1466, 1260, 1112. MS (ESI, 100% MeOH): m/e 802.0 {[M+Na]⁺, 100%}, 779.1 (M⁺, 12 70%). Anal. Calculated for $C_{24}H_{57}O_{13}Si_8$ (found): C, 37.03 (36.92), H, 7.38 (7.54). □13 ወ ጠ14 Preparation of $[((c-C_6H_9)SiO_{1.5})_4((c-C_6H_9)(OH)SiO_{1.0})_2((CH_2=CH)(OH)SiO_{1.0})_1]_{\Sigma_7}$: ₩15 ₩16 ₩16 ₩17 A solution of 35% aqueous NEt₄OH (0.1 mL, 0.25 mmol) was added to a solution of [(c- C_6H_9 SiO_{1.5}] Σ_6 (205 mg, 0.25 mmol) and VinylSi(OMe)₃ in THF (2.5 mL). The solution was stirred for 1 h then neutralized with dilute aqueous HCl. Evaporation of the volatiles afforded a white resin, which was dissolved in Et₂O and dried over anhydrous MgSO₄. Filtration and evaporation of the solvent afforded a white solid in high mass yield. multinuclear NMR spectroscopy and electrospray mass spectrometry indicated that the product mixture contained a $\sim 6:1$ mixture of $[((c-C_6H_9)SiO_{1.5})_2((c-C_6H_9)(OH)SiO_{1.0})_4]$ and $[((c-C_6H_9)SiO_{1.5})_4((c-C_6H_9)(OH)SiO_{1.0})_2((CH_2=CH)(OH)SiO_{1.0})_1]_{\Sigma_7}. \ \ Selected \ \ characterization$ data: 29 Si $\{^{1}$ H $\}$ NMR (99.3 MHz, CDCl₃, 25 °C) δ -60.1 (s, 2 Si, Cy-Si-OH), -68.2 (s, 1 Si), -23 69.1 (s, 2 Si), -69.7 (s, 1 Si), -72.0 (s, 1 Si, V-Si-OH). 1 H NMR (500 MHz, CDCl₃, 25 $^{\circ}$ C) δ 24 5.90 (m, 3 H, -CH=CH₂); 1.65, 1.16 (m, 66 H, C_5H_{11}). $^{13}C\{^1H\}$ NMR (125.8 MHz, C_6D_6 , 25 25 °C) δ 135.4 (s, =CH₂); 130.4 (s, -CH=); 27.53, 27.47, 26.82, 26.67, 26.59, 26.56 (s, CH₂); 26 23.81, 23.59, 23.36, 23.10 (s, CH). MS (ESI, 100% MeOH): m/e 917 ([M + H]⁺, 75%); 939 27 $({M + Na}^+, 100)$ 28 Reaction of $[((c-C_6H_{11})SiO_{1.5})_6]_{\Sigma_6}$ with NEt₄OH at room temperature: A solution 29 of $[((c-C_6H_{11})SiO_{1.5})_6]_{\Sigma_6}$ (200 mg, 0.24 mmol) and 35% aqueous NEt₄OH (0.1 mL, 0.25 30 mmol) in THF (2.5 mL) was stirred at 25 °C for 4 h then neutralized with dilute aqueous HCl. 31 Evaporation of the volatiles afforded a white solid, which was dissolved in Et₂O and dried 32 over anhydrous MgSO₄. Filtration and evaporation of the solvent afforded a white solid in

high mass yield. Analysis of the product mixture by ²⁹Si NMR spectroscopy indicated that it 1 $[((c-C_6H_{11})SiO_{1.5})_2(c-C_6H_{11})(OH)SiO_{1.0})_4]_{\Sigma_6}$ (>60%)and [((c-2 contained mainly 3 C_6H_{11} SiO_{1.5})₄(c-C₆H₁₁)(OH)SiO_{1.0})₃]_{Σ7} (>30%). of $[((c-C_6H_{11})SiO_{1.5})_6((c-C_6H_{11})(OH)SiO_{1.0})_2]_{\Sigma_8}$ [((c-**Preparation** 4 $C_6H_{11})SiO_{1.5}_{8}]_{\Sigma_8}$: A solution of $[((c-C_6H_{11})SiO_{1.5})_8]_{\Sigma_8}$ (250 mg, 0.23 mmol) and 35% 5 aqueous NEt4OH (0.1 mL, 0.25 mmol) in THF (3 mL) was stirred at room temperature for 1 6 h and then neutralized with an aqueous solution of HCl. The volatiles were evaporated in 7 vacuo to afford a white solid, which was dissolved in Et₂O and dried over anhydrous MgSO₄. 8 Filtration and evaporation of the solvent afforded a white microcrystalline solid in high yield. 9 Analysis by ²⁹Si NMR spectroscopy and electrospray MS indicated that the product mixture 10 contained ~76% (by ²⁹Si NMR) $[((c-C_6H_{11})SiO_{15})_6((c-C_6H_{11})(OH)SiO_{10})_2]_{\Sigma_8}$: ²⁹Si{¹H} NMR 11 _12 (99.3 MHz, C₆D₆, 25 °C) δ -60.4, -67.2, -69.8 (s, 1:1:2), as well as smaller amounts of 型13 型14 型15 型15 型16 unreacted $[((c-C_6H_{11})SiO_{1.5})_8]_{\Sigma_8}$ (δ -68.2, ~20%). Small ²⁹Si NMR resonances attributable to tetrasilanol $[((c-C_6H_{11})SiO_{1.5})_6((c-C_6H_{11})(OH)SiO_{1.0})_2]_{\Sigma_8}$ were also observed, as well as prominent peaks in the electrospray mass spectrum for the [((c-C₆H₁₁)SiO_{1.5})₆((c- $C_6H_{11})(OH)SiO_{1.0})_2]_{\Sigma_8}$ (1117.36 for the ion with H+ and 1139 for the ion with Na+). 17 18 18 19 520 Spectroscopic data for $[((c-C_6H_{11})SiO_{1.5})_6((c-C_6H_{11})(OH)SiO_{1.0})_2]_{\Sigma_8}$ matched the data previously reported for this compound. $[((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}$ from **Preparation** of [((c- C_6H_{11})SiO_{1.5})₈] Σ_8 : A solution of [((c-C₆H₁₁)SiO_{1.5})₈] Σ_8 (500 mg, 0.46 mmol) and 35% aqueous NEt4OH (0.2 mL, 0.49 mmol) was refluxed in THF (5 mL) for 4 h then neutralized 21 22 with dilute aqueous HCl. Evaporation of the volatiles afforded a white solid, which was dissolved in Et2O and dried over anhydrous MgSO4. Filtration and evaporation of the 23 solvent afforded $[((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}$ as a white microcrystalline 24 solid in 23% yield. Spectroscopic data for the product matched the data previously reported 25 for samples of $[((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}$ obtained via the hydrolytic 26 27 condensation of c-C₆H₁₁SiCl₃. $[((c-C_6H_{11})SiO_{1.5})_2((c-C_6H_{11})(OH)SiO_{1.0})_4]_{\Sigma_6}$ 28 **Preparation** of from [((c-29 C_6H_{11} SiO_{1.5})_{[28}: A solution of $[((c-C_6H_{11})SiO_{1.5})]_{\Sigma_8}$ (200 mg, 0.24 mmol) and 35% 30 aqueous NEt4OH (0.2 mL, 0.49 mmol) in THF (5 mL) was stirred at 25 °C for 1 h then

neutralized with dilute aqueous HCl. Evaporation of the volatiles afforded a white solid,

- which was dissolved in Et₂O and dried over anhydrous MgSO₄. Filtration and evaporation 1 2 of the solvent afforded $[((c-C_6H_{11})SiO_{1.5})_2((c-C_6H_{11})(OH)SiO_{1.0})_4]_{\Sigma_6}$ as a white solid in 63% yield (135 mg). ²⁹Si{¹H} NMR (99.3 MHz, CDCl₃, 25 °C) δ -59.4, -68.8 (s, 2:1). ¹H NMR 3 (500 MHz, CDCl₃, 25 °C) δ 1.78 (v br m); 1.7 (v br m). ¹³C{¹H} NMR (125.8 MHz, CDCl₃, 4 5 25 °C) $\delta = 27.55$, 27.47, 26.86, 26.62(CH₂); 23.68, 23.16 (2:1, SiCH). MS (ESI, 100%) MeOH): m/e 846 (M+H⁺, 48%); M+Na⁺, 95%); 885 (M⁺ - H + K, 100%). 6 Preparation of $[((C_6H_5CH=CH)SiO_{1.5})_6((C_6H_5CH=CH)(OH)SiO_{1.0})_2]_{\Sigma_8}$ 7 from $[((C_6H_5CH=CH)SiO_{16})_8]_{\Sigma_8}$: CH₂Cl₂/i-PrOH/THF(4/4/4 solution 8 Α mL) of 9 $[((C_6H_5CH=CH)SiO_{15})_8]_{\Sigma_8}$ (124.2 mg, 0.10 mmol) was added an aqueous solution of Et₄NOH 10 (35%, 49.4 mL, 0.12 mmol) at -35 °C. After addition the resulting mixture was stirred at the 11 same temperature for 5 h. The mixture was neutralized with 1N HCl solution and extracted 12 12 13 14 015 16 17 17 18 19 20 with diethyl ether. The organic layer was washed with brine, dried over Na₂SO₄, and evaporated. The residue was passed through a silica gel column using hexane/Et₂O (2:1) as of an eluent. **Evaporation** the volatiles gave $[((C_6H_5CH=CH)SiO_{1.5})_6((C_6H_5CH=CH)(OH)SiO_{1.0})_2]_{\Sigma_8}$ (112.4 mg, 0.09 mmol) as a white solid in 89% yield. ¹H NMR (CDCl₃) δ 5.83 (br s, 2H), 6.31-6.45 (m, 16H), 7.21-7.59 (m, 40H). ¹³C NMR (CDCl₃) δ 117.41, 117.76, 117.96, 126.90, 128.43, 128.50, 128.53, 128.75, 128.83, 128.90, 137.17, 137.23, 137.29, 149.11, 149.15, 149.21. ²⁹Si NMR (CDCl₃) δ – 78.05, -77.05, -68.66. $[((C_6H_5CH_2CH_2SiO_{1.6})_6((C_6H_5CH_2CH_2)(OH)SiO_{1.6})_2]_{\Sigma_8}$ Preparation of CH₂Cl₂/*i*-PrOH/THF 21 $[((C_6H_5CH_2CH_2)SiO_{15})_8]_{\Sigma_8}$: (5/5/5 mL) Α of 22 $[((C_6H_5CH_2CH_2)SiO_{15})_8]_{\Sigma_8}$ (251.6 mg, 0.20 mmol) was added an aqueous solution of Et₄NOH 23 (35%, 247.0 L, 0.60 mmol) at -35 °C. After addition the resulting mixture was stirred at the 24 same temperature for 4 h. The mixture was neutralized with 1N HCl solution and extracted 25 with diethyl ether. The organic layer was washed with brine, dried over MgSO₄, and
 - evaporated. The residue was passed through a silica gel column using hexane/Et₂O (2:1) as an eluent. Evaporation of the volatiles gave pure
 - 28 $[((C_6H_5CH_2CH_2SiO_{1.5})_6((C_6H_5CH_2CH_2)(OH)SiO_{1.0})_2]_{\Sigma_8}$ (225.3 mg, 0.18 mmol) as a colorless
 - 29 oil in 88% yield. ¹H NMR (CDCl₃) δ 1.11-1.25 (m, 16H), 2.86-2.98 (m, 16H), 5.24 (br s,
 - 30 2H), 7.25-7.47 (m, 40H). ¹³C NMR (CDCl₃) δ 13.56, 14.19, 14.30, 28.90, 28.95, 28.98,

125.74, 125.84, 127.71, 127.83, 128.29, 128.33, 128.42, 143.67, 143.75, 143.78. ²⁹Si NMR 1 2 $(CDCl_3) \delta -67.75, -65.99, -58.35.$ of $[((CH_3C_6H_4SiO_{15})_6((CH_3C_6H_5)(OH)SiO_{10})_2]_{\Sigma_8}$ from 3 **Preparation** that for procedure similar to used $[((CH_3C_6H_5)SiO_{15})_8]_{\Sigma_8}$: Α 4 $[((C_6H_5CH_2CH_2SiO_{_{1.5}})_6((C_6H_5CH_2CH_2)(OH)SiO_{_{1.0}})_2]_{\Sigma8}$ used to produce was 5 $[((CH_{3}C_{6}H_{4}SiO_{1.5})_{6}((CH_{3}C_{6}H_{5})(OH)SiO_{1.0})_{2}]_{\Sigma 8}. \quad ^{1}H \ NMR \ (CDCl_{3}) \ \delta \ 2.36 \ (s, \ 6H), \ 2.41 \ (s, \ 6H)_{1.5}$ 6 12H), 2.42 (s, 6H), 6.03 (br s, 2H), 7.08 (d, $^{3}J = 7.5$ Hz, 4H), 7.16 (d, $^{3}J = 7.5$ Hz, 8H), 7 $7.24 \text{ (d, }^{3}J = 7.5 \text{ Hz, 4H)}, 7.56 \text{ (d, }^{3}J = 7.5 \text{ Hz, 4H)}, 7.62 \text{ (d, }^{3}J = 7.5 \text{ Hz, 8H)}, 7.72 \text{ (d, }^{3}J = 7.5 \text{ Hz$ 8 7.5 Hz, 4H). ¹³C NMR (CDCl₃) δ 21.50, 21.53, 21.56, 127.10, 127.29, 127.65, 128.41, 9 128.48, 128.53, 134.25, 140.26, 140.31, 140.56. ²⁹Si NMR (CDCl₃) δ -78.22, -76.86,-10 69.05. MS (ESI, 100% MeOH): m/z Calcd for $C_{56}H_{58}O_{13}Si_8Na$ (100%): 1185.2. Found: 11 112 12 13 13 14 14 15 1185.4. C₅₆H₅₈O₁₃Si₈H (20%): 1163.2. Found: 1163.5. C₅₆H₅₈O₁₃Si₈K (20%): 1201.2. Found: 1201.3. Preparation of $[(c-C_6H_{11}SiO_{1.5})_6((c-C_6H_{11})(OH)SiO_{1.0})_2]_{\Sigma 8}$ from $[(c-C_6H_{11}SiO_{1.5})_8]_{\Sigma 8}$: A THF (100 mL) solution of $[(c-C_6H_{11}SiO_{15})_8]_{\Sigma8}$ (5.41 g, 5.00 mmol) was added a methanol 16 solution of Me₄NOH (25%, 1.90 mL, 4.50 mmol) at room temperature. After addition the 17 18 18 19 19 120 resulting mixture was stirred at the same temperature for 1 h. The mixture was neutralized with 1N HCl solution and extracted with diethyl ether. The organic layer was washed with brine, dried over MgSO₄, and evaporated. The residue was passed through a silica gel column using hexane and CH2Cl2 as an eluent. Evaporation of the volatiles gave pure [(c- $C_6H_{11}SiO_{1.5})_6((c-C_6H_{11})(OH)SiO_{1.0})_2]_{\Sigma 8}$ (4.60 g, 4.18 mmol) as a white solid in 84% yield. ¹H 21 NMR (500 MHz, CDCl₃, 25 °C): δ 4.30 (br s, SiOH, 2H), 1.76 (br m's, 40H), 1.23 (br m's, 22 40H), 0.74 (br m's, 8H). ¹³C{¹H} NMR (125 MHz, CDCl₃, 25 °C): δ 27.55, 27.48, 26.88, 23 26.79, 26.58, 26.53 (CH₂), 23.79, 23.69, 23.07 (4:2:2 for CH), ²⁹Si{¹H} NMR (99 MHz, 24 CDCl₃, 25 °C): δ -59.91, -67.60, -69.85 (2:2:4). IR (25 °C, KBr, cm⁻¹): 2916, 2838, 1447, 25 1197, 1109. MS (70 eV, 200 °C, relative intensity): m/e 1015 ([M - $(C_6H_{11})]^+$, 100). Anal. 26 Calcd for $C_{48}H_{90}O_{13}Si_8$ (found): C, 52.42 (52.32), H, 8.25 (8.68). 27 Reaction of $[((CH_3)_2CHCH_2)SiO_{1.5})_8]_{\Sigma_8}$ with NEt₄OH at room temperature. A 28 solution of 35% NEt₄OH in water (0.11 mL, 0.25 mmol) was added to a THF (5 mL) solution 29 of $[((CH_3)_2CHCH_2)SiO_{1.5})_8]_{\Sigma_8}$ (0.20 g, 0.23 mmol). The solution was stirred at room 30

temperature for 1 h and then neutralized with an aqueous solution of HCl. The THF was

removed in vacuo to afford a white oil, which was dissolved in Et2O, dried over anhydrous

MgSO₄ and filtered. Evaporation of the solvent afforded in 85% mass yield a milky white oil

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containing (by <sup>29</sup>Si NMR spectroscopy and ESI MS) unreacted [((CH<sub>3</sub>)<sub>2</sub>CHCH<sub>2</sub>)SiO<sub>1.5</sub>)<sub>8</sub>]<sub>Σ8</sub>
       1
                                                                                                                                                                                    (29\%),
                                                   [((CH_1)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}
       2
                (9%),
                [((CH_3)_2CHCH_2)SiO_{1.5})_6((CH_3)_2CHCH_2)(OH)SiO_{1.0})_2]_{\Sigma_8}
                                                                                                                                                                                          and
       3
                [((CH_3)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.0})_4]_{\Sigma_8} (34%). Selected characterization data
       4
                for [((CH_2)_2CHCH_2)SiO_{1.5})_8]_{\Sigma_82}: <sup>29</sup>Si\{^1H\} NMR (99.3 MHz, C<sub>6</sub>D<sub>6</sub>, 25 °C) \delta -67.6; MS (ESI,
       5
                                                                                                                          (M+H^{+},
                                                                                                      873
                                                                                                                                                      5%).
       6
                100%
                                        MeOH):
                                                                     m/e
                [((CH_3)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3
       7
                °C) \delta -58.9, -67.1, -68.5 (3:1:3); MS (ESI, 100% MeOH): m/e: _3 791 (M+H^+, 2%) and 813
       8
                (M+Na^{+}, 5\%). For [((CH_{3})_{2}CHCH_{2})SiO_{1.5})_{6}((CH_{3})_{2}CHCH_{2})(OH)SiO_{1.0})_{2}]_{\Sigma_{8}}: <sup>29</sup>Si\{^{1}H\} NMR
       9
                (99.3 MHz, C<sub>6</sub>D<sub>6</sub>, 25 °C) δ -59.6, -66.8, -68.7 (1:1:2); MS (ESI, 100% MeOH): m/e 891
     10
                                                                                             913
                                                                                                                   (M+Na^{+},
                                                                                                                                                   5%).
                                                                                                                                                                                          For
                (M+H^{+},
                                              11%)
                                                                       and
11
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013
114
014
015
                [((CH_3)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.0})_4]_{\Sigma_8}: {}^{29}Si\{{}^{1}H\} NMR (99.3 MHz, C_6D_6, 25)_{1.5}
                °C) \delta (-58.4, -56.6, -66.5, -68.3, 1:1:1:1); MS (ESI, 100% MeOH): m/e 909 (M+H<sup>+</sup>, 15%)
                and 931 (M+Na<sup>+</sup>, 100%).
                                                                   [((CH_3)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}
                              Preparation
                                                         of
16
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18
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                [((CH_3)_2CHCH_2)SiO_{1.5})]_{\Sigma_8}: A solution of [((CH_3)_2CHCH_2)SiO_{1.5})]_{\Sigma_8} (400 mg, 0.46 mmol)
                and 35% aqueous NEt<sub>4</sub>OH (0.2 mL, 0.49 mmol) was refluxed in THF (5 mL) for 4 h then
                neutralized with dilute aqueous HCl. Evaporation of the volatiles afforded a white resin,
                which was dissolved in Et<sub>2</sub>O and dried over anhydrous MgSO<sub>4</sub>. Filtration and evaporation of
□ 20
                the solvent afforded crude [((CH_3)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.5})_3]_{\Sigma_7} as a white
                resinous substance in 44% yield. Colorless crystals were obtained by recrystallization from
     21
                                                                                                                                                                                            for
                                                                                                                      characterization
                                                                                                                                                                   data
                acetonitrile/toluene.
                                                                                      Selected
     22
                [((CH_3)_2CHCH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}: {}^{29}Si\{{}^{1}H\} \ NMR \ (99.3 \ MHz, \ C_6D_6, \ 25)_3((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3
     23
                 °C) \delta -58.5, -66.9, -68.3 (s, 3:1:3). <sup>1</sup>H NMR (500 MHz, C<sub>6</sub>D<sub>6</sub>, 25 °C) \delta 2.21 (m, 7 H, -CH-);
     24
                 1.24 (d, J = 6.6 Hz, 18 H, CH_3); 1.21 (d, J = 6.6 Hz, 18 H, CH_3); 1.17 (d, J = 6.6 Hz, 6 H,
     25
                CH_3); 0.97 (d, J = 7.1 Hz, 6 H, CH_2); 0.95 (d, J = 7.1 Hz, 6 H, CH_2); 0.92 (d, J = 7.0 Hz, 2 H,
     26
                CH<sub>2</sub>). {}^{13}C\{{}^{1}H\} NMR (125.8 MHz, C_6D_6, 25 °C) \delta = 25.7 (s, CH<sub>3</sub>); 25.6 (s, CH<sub>3</sub>); 25.5 (s,
     27
                 CH<sub>3</sub>); 24.1 (s, CH<sub>2</sub>); 24.05 (s, CH<sub>2</sub>); 24.0 (s, CH<sub>2</sub>); 23.4 (s, CH); 23.0 (s, CH); 22.6 (s, CH).
     28
                MS (ESI, 100% MeOH): m/e 791.16 (M+H<sup>+</sup>, 80%); 813.08 (M+Na<sup>+</sup>, 100%). A single crystal
     29
                 X-ray diffraction study was also performed.
     30
                               Preparation of [((CH_3)_2CHCH_2)SiO_{1.5})_6((CH_3)_2CHCH_2)(OH)SiO_{1.0})_2]_{\Sigma_8}
                                                                                                                                                                                       from
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A reactor was charged with 2126g (2.438 moles) 1 $[((CH_3)_2CHCH_2)SiO_{1.5})_8]_{\Sigma_8}$: $[((CH_3)_2CHCH_2)SiO_{1.5})_8]_{\Sigma 8}$ and 20 L THF. A basic solution of Me₄NOH (48 mL, 25 wt %, in 2 MeOH) and THF (4 L) was cooled to 0 °C and added slowly (3.5 hours) to the reaction 3 followed by 1 hour of stirring. Product formation was monitored by HPLC and upon 4 completion was quenched into 320 mL conc. HCl and 700 mL H2O at 0 °C. Evaporation of 5 the resulting solution gave waxy solids, that were washed with water until a pH = 7 and 6 recrystallized using acetone and acetonitrile to produce 1525 g (70% yld) of product at 98% 7 purity. ¹H NMR (CDCl₃): 3.99 (2 H, 2 x OH, bs); 1.85 (8 H, 8 x CH, m); 0.95 (48 H, 16 x 8 CH₃, m); 0.60 (16 H, 8 x CH₂, m). ${}^{1}H{}^{13}C$ NMR (CDCl₃): 25.80; 25.75; 25.65; 23.99; 9 23.93; 23.86; 23.07; 22.46. Note that the above procedure can be adapted to both continuous 10 and batch production methods to produce the desired product higher yield and greater purity. 11

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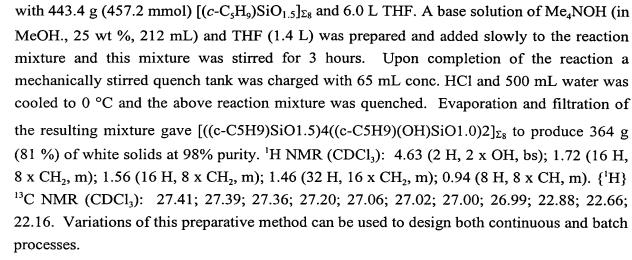
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Preparation of $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})_6((CH_3)_2CHCH_2)(OH)SiO_{1.0})_2]_{\Sigma_R}$ from $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})]_{\Sigma_n} = 8$, 10: A reactor was charged with 128.0 g (96.82 mmol [((CH₃)₂CH₂CHCH₃CH₂)SiO_{1.5})] $_{\rm n}$ and 2080 mL THF. A basic solution 48 mL (25 wt %, in MeOH) of Me₄NOH was cooled to 0 °C and added to the reaction mixture over 45 minutes and stirred for an additional 1.5 hour. Reaction progress was monitored by HPLC and at completion the reaction was quenched into HCl (150 mL, 1 N) and hexane (500 mL) with rapid stirring over a period of 1 hour. The top layer was removed and evaporated to give 125.7 g (97 %) of the colorless liquid product. ¹H NMR (CDCl₃): 1.83 (9.3, bm); 1.27 (9.8, bm); 1.15 (10, bm); 1.00 (23, m); 0.89 (64, s); 0.85 (7.7, s); 0.73 (8.1, bm); 0.58 (8.0, bm). {¹H} ¹³C NMR (CDCl₃): 54.50; 54.37; 31.19; 30.22; 29.48; 25.59; 25.49; 25.30; 25.22; 25.00; 24.36; 24.29.

Preparation of [((CH₃)₂CH₂CHCH₃CH₂)SiO_{1.5})₄((CH₃)₂CHCH₂)(OH)SiO_{1.0})₃]₂₇ from $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})]_{\Sigma_n} = 8$, 10: A similar procedure to that reported above for $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})_6((CH_3)_2CHCH_2)(OH)SiO_{1.0})_2]_{\Sigma_8}$ can be using LiOH in acetone to prepare an oily trisilanol product that contains 95% of two trisilanol species $[((CH_3)_2CH_2CHCH_3CH_2)SiO_{1.5})_4((CH_3)_2CHCH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}$ and $[((CH_3)_2CH_2CHCH_3CH_2)$ $SiO_{1.5}$ ₆((CH₃)₂CHCH₂)(OH)SiO_{1.0})₃]_{Σ_9} ¹H NMR (500 MHz, CDCl₃): δ (ppm) 0.562 (m, 1 H), 0.755 (m, 1 H), 0.908 (s, 9 H), 1.002 (m, 3 H), 1.137 (m, 1 H), 1.303 (m, 1 H), 1.831 (m, 1 H), 6.240 (br, 3 H); ¹³C NMR (125 MHz, CDCl₃): δ(ppm) 24.06, 24.51, 24.86, 25.44, 25.59, 25.65, 25.89, 29.65, 29.90, 30.64, 30.68, 31.59, 32.02, 54.28, 54.77; ²⁹Si NMR (99.4 MHz, CDCl₃): δ (ppm) -68.66, -68.43, -67.54, -67.32, -58.75, -57.99. EIMS: m/e 1382 (22%, M⁺(T₉) - iOct - H_2O), 1052 (100%, $M^+(T_7)$ - iOct - H_2O).

from $[((CH_3CH_2)SiO_{1.5})_4((CH_3CH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}$ 1 **Preparation** [((CH₃CH₂)SiO_{1.5})]_{Σ_8}: A solution of 35% NEt₄OH in water (0.2 mL, 0.49 mmol) was added 2 to a THF (5 mL) solution of $[((CH_3CH_2)SiO_{1.5})]_{\Sigma_8}$ (0.41 g, 0.46 mmol). The solution was 3 refluxed for 7 h and then neutralized with an aqueous solution of HCl. The THF was removed 4 in vacuo affording a colorless oil, which is dissolved in Et2O and dried over MgSO4 5 anhydrous. Evaporation of the solvent in vacuo and crystallization from MeOH afforded 6 $[((CH_3CH_2)SiO_{1.5})_4((CH_3CH_2)(OH)SiO_{1.0})_3]_{\Sigma_7}$ as a white solid. Selected characterization data: 7 29 Si{ 1 H} NMR (99.3 MHz, C₆D₆, 25 °C) δ = -56.4, -64.8, 65.9 (3:1:3MS (ESI, 100%) 8 MeOH): m/e: 595 (M+H⁺, 100%); 617 (M+Na⁺, 60%). 9 Preparation $[((CH_3)SiO_{1.5})_4((CH_3)(OH)SiO_{1.0})_3]_{\Sigma_7}$ from $[((CH_3)SiO_{1.5})_8]_{\Sigma_8}$: A THF 10 (350 mL) suspension of $[((CH_3)SiO_{1.5})_8]_{\Sigma_8}$ (8.5 g, 15.83 mmol) was added an aqueous 11 □12 ⑤ ①13 solution of Et₄NOH (35%, 6.51 mL, 15.83 mmol) at room temperature. After addition the resulting mixture was stirred at the same temperature for 20 h. The mixture was 型 14 型 15 型 16 型 17 型 18 手 19 三 20 neutralized with 1N HCl solution and extracted with diethyl ether. The organic layer was washed with brine, dried over MgSO4. Evaporation of the volatiles gave a white oil-like solid. Recrystallization of the white solid from a mixed solvent (MeOH/H₂O = 2.5/1) afforded [((CH₃)SiO_{1.5})₄((CH₃)(OH)SiO_{1.0})₃]_{Σ7} (1.35 g, 2.72 mmol)as a white powder in 17% yield. ¹H NMR (CDCl₃) δ 0.13 (s, 9H), 0.14 (s, 3H), 0.15 (s, 9H), 6.11(s, 3H). ¹³C NMR (CDCl₃) δ -4.50, -4.35. ²⁹Si NMR (CDCl₃) δ -65.70, -65.16,-55.84. Calcd for C7H24O12Si7: C, 16.92; H, 4.87. Found: C, 17.16; H, 4.89. MS (ESI, 100% MeOH): *m/e*: 496.96 (M+H⁺, 100%); 518.86 (M+Na⁺, 75%). 21 22 $[((c-C_6H_{11})SiO_{1.5})_4((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}$ from [((c-**Preparation** C_6H_{11})SiO_{1.5})₇((H) SiO_{1.0})₁] Σ_8 : A solution of [((c-C₆H₁₁)SiO_{1.5})₇((H)SiO_{1.0})₁] Σ_8 (460 mg, 0.46 23 mmol) and 35% aqueous NEt₄OH (0.2 mL, 0.49 mmol) was refluxed in THF (5 mL) for 5 h 24 then neutralized with dilute aqueous HCl. Evaporation of the volatiles afforded a white solid, 25 26 which was dissolved in Et₂O and dried over anhydrous MgSO₄. Filtration and evaporation of 27 the solvent afforded a white microcrystalline solid in high yield. Analysis of the product mixture by 29 Si NMR spectroscopy indicated that the major product was [((c-28 $C_6H_{11})SiO_{1.5}$ ₄ $((c-C_6H_{11})(OH)SiO_{1.0})_3]_{\Sigma_7}$; small amounts of $[((c-C_6H_{11})SiO_{1.5})]_{\Sigma_8}$ were also 29 30 present. 31 Preparation $[((c-C_5H_9)SiO_{1.5})_4((c-C_5H_9)(OH)SiO_{1.0})_2]_{\Sigma_8}$ from $[(c-C_5H_9)SiO_{1.5}]_{\Sigma_8}$: A

12-L reactor equipped with a mechanical stirrer, addition pump and drying tube, was charged



Although the present invention has been described above in terms of specific embodiments, it is anticipated that alterations and modifications thereof will no doubt become apparent to those skilled in the art. It is therefore intended that the following claims be interpreted as covering all such alterations and modifications as fall within the true spirit and scope of the invention.

What is claimed is: